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New Target Methodology: Polymer-Assisted Deposition and Its

Applications on Gas-Phase Nuclear Chemistry with Rutherfordium

by

Mitch André Garcia

A dissertation submitted in partial satisfaction of the

requirements for the degree of

Doctor of Philosophy

in

Chemistry

in the

Graduate Division

of the

University of California, Berkeley

Committee in charge:

Professor Heino Nitsche, Chair

Professor Joseph Cerny

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Fall 2009

The dissertation of Mitch André Garcia, titled New Target Methodology: Polymer-Assisted Deposition and Its Applications on Gas-Phase Nuclear Chemistry with Rutherfordiumthe is approved:

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New Target Methodology: Polymer-Assisted Deposition and Its Applications on Gas-Phase

Nuclear Chemistry with Rutherfordium

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by

Mitch André Garcia

Abstract

New Target Methodology: Polymer-Assisted Deposition and Its Applications on Gas-Phase Nuclear Chemistry with Rutherfordium

by

Mitch André Garcia Doctor of Philosophy of Chemistry University of California Berkeley Professor Heino Nitsche, Chair

This work focuses on three research topics that were distinctly different but broadly centered around developing new methods to perform transactinide gas-phase chemistry. First, the application of a new materials science methodology, Polymer-Assisted Deposition (PAD), to target manufacturing is described. Second, the construction of a new experimental apparatus to conduct gas-phase chemistry and the design of circuits and electronics for the measurement of alpha-decay energy is discussed. Third, a new nuclear reaction for the production of 261 Rf, an ideal candidate for gas-phase chemistry due to its relatively-long half life ($t_{1/2} = 69$ s), is detailed.

The PAD method was used to make metal oxides of hafnium, europium, and thulium on silicon backings that were found to be homogenous and highly uniform metal oxide films. The films, after a single application of the PAD method, ranged in thickness from 30 to 320 nm. The reapplication of the PAD method on already existing metal oxide films (six times) using the 10% by weight hafnium (IV) solution resulted in equally homogeneous and uniform films with a total thickness of 600 nm.

The irradiation of targets made by the PAD method on silicon nitride backings (thickness

of 1000 nm, 344 μ g/cm²) were irradiated with an ⁴⁰Ar beam at a laboratory frame energy of 210 MeV (50 particle nA). The root mean squared (RMS) roughness prior to irradiation was 1.1 nm for a 250 nm (220 μ g/cm²) Tm₂O₃ target, and a RMS roughness of 2.0 nm after irradiation was measured by Atomic Force Microscopy (AFM). These experiments demonstrated the resilience of the targets to heavy-ion irradiation and will prove useful when next generation ion sources come online with subsequently larger beam intensities.

The design, construction and testing of the alpha-wheel apparatus for gas-phase chemistry reactions was completed. Testing of the device was done with ²⁰⁵Fr, produced from the nuclear reaction of ¹⁶⁹Tm(⁴⁰Ar, 4n)²⁰⁵Fr. The francium atoms were quickly transported to the alpha-wheel apparatus, and a total of 164 decays were detected. They centered at an energy of 6.8 MeV which corresponded to the known 7.01 MeV alpha particle from ²⁰⁵Fr; discrepancies in the energy are due to energy-loss from the helium atmosphere in the apparatus.

The first nuclear synthesis of Rutherfordium-261 using uranium targets (²³⁸U) were conducted with the Berkeley Gas-filled Separator at the Lawrence Berkeley National Laboratory 88-Inch Cyclotron. The nuclear reaction consisted of irradiating the uranium targets with a ²⁶Mg beam. The production of ²⁶¹Rf went through a 3n exit channel, a channel not normally seen in hot-fusion reactions, and had a cross section of 28 pb.

In summary, this work shows that Polymer-Assisted Deposition is a good method to produce homogeneous, uniform, and crack-free metal oxide targets for nuclear science applications. It also showed that the construction of an alpha-wheel apparatus to measure the alpha-decay of radionuclides is reliable. Finally, it has been shown that the production of ²⁶¹Rf is possible with uranium targets at a sufficient cross-section to make a gas-phase chemistry reaction with this isotope feasible.

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Chapter 1: Target Methodology and Rutherfordium Chemistry

1.1.1 Introduction

This dissertation is concerned with the study of a new target methodology with applications to transactinide chemistry, the construction of a gas-phase transactinide element chemistry apparatus, and the study of a new transactinide production reaction for ²⁶¹Rf. The transactinides comprise the elements between rutherfordium (Z = 104) to the recently confirmed element 114; they are found in the last period of the Periodic Table in Groups 4 through 14, and can be seen in Figure 1.1.¹ All the transactinides are inherently unstable to nuclear decay and, depending on the isotope, will decay by either alpha-decay, beta-decay, or spontaneous fission; the longest-living confirmed isotope has a half-life of ~1 min (Rf²⁶¹, T_{1/2}=75 s).² All transactinides are produced in a particle accelerator, whereby a beam of heavy-ions is accelerated and directed at a target; on occasion an atomic nucleus of the beam and target will fuse to form a compound nucleus of the transactinide of interest (several methods nuclear scientists use to produce targets are discussed in section 1.2.). The probability of producing the desired compound nucleus is very small; a sample calculation of the probability to produce a transactinide element is given later in this section.

The study of an element's chemistry is at the heart of all chemistry research. Chemists who study the chemical properties of the transactinides have to verify that the newly discovered elements indeed behave as one would expect for a member of their respective group on the Periodic Table. Deviations from predicted behavior need to be explored, and some examples of deviations are discussed in section 1.4. Because of the low probability of producing transactinide elements it is necessary to study their chemistry at an atom-at-a-time basis. This is usually done by separating the element of interest from the beam using velocity filters and/or

1

magnetic rigidity separators; this is discussed in more detail in chapter 5.

1 H 1	2											13	14	15	16	17	18 He 2
Li	Be											B	Ç	N	Q	F	Ne
Na 11	Mg 12	3	4	5	6	7	8	9	10	11	12	Al 13	6 Si 14	P 15	8 S 16	9 Cl 17	Ar 18
K 19	Ca 20	Sc_{21}	Ti 22	V 23	Cr 24	$\underset{25}{\operatorname{Mn}}$	Fe 26	Co 27	Ni 28	Cu 29	Zn 30	Ga 31	Ge 32	As 33	Se 34	Br 35	Kr 36
Rb 37	Sr 38	Y 39	Zr 40	Nb 41	Mo 42	Tc 43	Ru_{44}	Rh 45	Pd 46	Ag 47	Cd 48	In 49	Sn 50	Sb 51	Te 52	I 53	Xe 54
Cs 55	Ba 56	La 57	Hf 72	Ta 73	W 74	Re 75	Os 76	Ir 77	Pt 78	Au 79	Hg 80	T1 81	Pb 82	Bi 83	Po 84	At 85	Rn 86
Fr 87	Ra 88	Ac 89	Rf 104	Db 105	Sg 106	$_{ m 107}^{ m Bh}$	Hs 108	Mt 109	Ds 110	$\underset{111}{\operatorname{Rg}}$	Cn 112		114				

Ce	Pr	Nd	Pm	Sm	Eu	Gd	Tb	Dy	Ho	Er	Tm	Yb	Lu
58	59	60	61	62	63	64	65	6ĕ	67	68	69	70	71
Th	Pa	U	Np	Pu	Am	Cm	Bk	Cf	Es	Fm	Md	No	Lr
90	91	92	93	94	95	96	97	98	99	100	101	102	103

Figure 1.1 Current periodic table of the elements as of November 2009.

In a nuclear reaction, a target comprised of stationary nuclei is irradiated with heavy-ion beams (*i.e*, ¹⁸O, ²²Ne, ²⁶Mg, ⁴⁸Ca) as shown schematically in Figure 1.2.



Figure 1.2 Schematic diagram of beam particles (P) going through a target (T).

The energy of the beam is often characterized in the literature as a value in the laboratory frame or as a value in the center-of-mass frame. In the laboratory frame, the projectile is characterized by its velocity, $V_{P,LF}$, and mass M_p , while the target nucleus is characterized by its velocity, $V_{T,LF}$ which equals zero, and has mass M_T . The total kinetic energy in the laboratory frame (T_{LF}) is thus,

$$T_{LF} = \frac{1}{2}M_P V_{P,LF}^2 + \frac{1}{2}M_T V_{T,LF}^2$$
(1.1a)

$$T_{LF} = \frac{1}{2}M_P V_{P,LF}^2 + 0 = \frac{1}{2}M_P V_{P,LF}^2$$
(1.1b)

Similarly the momentum ($P_{P,LF}$) for the projectile is given as $P_{P,LF} = M_P V_P$, and the momentum of the target nucleus is $P_{T,LF} = M_T V_T$ which is equal to zero in this reference frame. The center-ofmass frame is strictly defined as the system in which the total momentum of the projectile and target nucleus is zero. The velocity of the projectile and target nucleus in the center-of-mass frame are Galilean transformations from the laboratory frame, and are given respectively as thus,

$$V_{P,CM} = V_{P,LF} - V_{CM}$$
 (1.2a)

$$V_{T,CM} = V_{T,LF} + V_{CM} = V_{CM}$$
(1.2b)

The momentum in the center-of-mass frame (P_{CM}) is equal to $M_P(V_{P,LF} - V_{CM})$; since as the momentum of the projectile is also equal to the target's momentum, it is also equal to M_TV_{CM} . By solving for the velocity of the center of mass (V_{CM}), a transformation from one reference frame

to the other is possible. This can be accomplished by setting both values of the momentum in the center-of-mass frame equal to each other as thus,

$$M_P V_{P,LF} - M_P V_{CM} = M_T V_{CM}$$
 (1.3a)

$$M_P V_{P,LF} = (M_T + M_P) V_{CM}$$
 (1.3b)

$$V_{CM} = \frac{M_P V_{P,LF}}{(M_T + M_P)} \tag{1.3c}$$

Using this result it is trivial to then solve for the relationships between the center-of-mass momentum and laboratory frame momentum, and between the total kinetic energy in the centerof-mass and the laboratory frame.

$$P_{CM} = \frac{M_T P_{P,LF}}{(M_T + M_P)} \tag{1.4a}$$

$$T_{CM} = \frac{M_T T_{P,LF}}{(M_T + M_P)} \tag{1.4b}$$

On occasion a beam particle A will strike a nucleus of B. The rate, R, of this occurrence is given by Equation 1.5.

$$R = \sigma \Phi N_T \tag{1.5}$$

Where σ is the cross section, Φ is the flux density of beam particles A in units of cm⁻²s⁻¹, and N_T is the number of atoms of the target nuclide T. The cross section for simple scattering experiments can be described using the geometric cross section of the nucleus, which is on the order of 10⁻²⁴ cm² (ignoring nuclear forces and Coulomb interactions). Aside from scattering experiments, cross sections can be defined for specific nuclear reactions, and can be thought of

as a probability or likelihood that a nuclear reaction will occur. The unit for cross sections are called barns: 1 barn (b) = 10^{-24} cm².

A sample rate calculation for the production of rutherfordium isotopes is as follows. The production cross-sections for rutherfordium are on the order of nanobarns 10^{-33} cm², typical beam intensities available are ~ 10^{11} particles cm⁻²s⁻¹, and targets have ~ 10^{20} atoms within a typical area under irradiation. Multiplying these magnitudes together yields the rate of producing rutherfordium nuclei: somewhere on the order of ~0.01 s⁻¹ or 36 nuclei per hour.

To conduct a rutherfordium chemistry experiment, it is necessary to produce targets that do not flake, can withstand large intensities of heavy-ion beams, and are uniform and homogenous. Recently, there has been a push for higher intensity stable and radioactive beams at Coulomb barrier energies. In order to advance studies of nuclear structure, reactions, and astrophysics, experiments with new isotopes produced at the Facility for Rare Isotope Beams (FRIB) and the Argonne Tandem Linac Accelerator System (ATLAS) require higher energy and higher intensity beams, as outlined in the Nuclear Science Advisory Committee (NSAC) Long Range Plan for 2007.³ In the time leading up to the opening of the FRIB at Michigan State University, ATLAS at Argonne National Laboratory is being refit to provide a ten-fold intensity increase for all species.⁴ The upgrade will allow studies of nuclei from the very neutron-rich to those beyond the proton dripline. Other accelerators, such as the UNILAC, a linear accelerator at the Gesellschaft für Schwerionenforschung Institute (GSI) in Germany, also desire high beam intensities for super-heavy element research.⁵

Furthermore, it is necessary to construct instruments that will assist with the exploration of the chemistry from the collected rutherfordium atoms, and to develop electronic, circuits, and data acquisition systems to record their decay characteristics. Finally, new nuclear reactions should be investigated in order to look for alternative, more attractive, methods for producing long-lived rutherfordium isotopes (²⁶¹Rf).

1.2 Target Methodology

The preparation of targets has long occupied the time of experimental nuclear scientists. To date the main methods of creating targets are vacuum evaporation, molecular plating/electrodeposition, and painting/sedimentation. The work in this thesis will describe a new target methodology: polymer-assisted deposition. Each method is briefly described below.

One of the earliest reported uses of vacuum evaporation as a method to produce nuclear targets was by Randall and Smith in 1955.⁶ The method involves pasting an oxide or carbonate of an alkali or alkaline earth metal of interest onto a tantalum foil; the foil is then heated, and as the metal is reduced, the elemental form is collected on a cool assembly within the chamber. A schematic of this process is shown in Figure 1.3.



Figure 1.3 A generalized schematic of the evaporation method for target productions.⁷

The target thickness is a function of the rate of heating and the geometry of the vacuum evaporation apparatus. The chemical equations for this process with alkaline earth and alkali metals are given by Equation 1.6a-b and 1.7a-b respectively.

Alkaline Earth Metals

$$M_2O_{(s)} + heat \rightarrow 2M_{(s)} + \frac{1}{2}O_{2(g)}$$
 (1.6a)

$$M_2(CO_3)_{(s)} + heat \rightarrow 2M_{(s)} + CO_{2(s)} + \frac{1}{2}O_{2(g)}$$
 (1.6b)

Alkali Metals

$$MO_{(s)} + heat \rightarrow M_{(s)} + \frac{1}{2}O_{2(g)}$$
 (1.7a)

$$M(CO_3)_{(s)} + heat \rightarrow M_{(s)} + CO_{2(s)} + \frac{1}{2}O_{2(g)}$$
 (1.7b)

Molecular plating and electrodeposition are the electrochemist's solution to target preparation. Both methods employ an electrochemical cell with a solution comprised of the dissolved target metal of interest. Once a potential is applied across the cell, the solute deposits onto the target backing. Because both methods have a similar setup they are erroneously used interchangeably in the literature. In molecular plating, the molecular compound that is dissolved in the electrolyte is deposited onto the surface, while in electrodeposition it is the elemental form of the element. Another difference is the use of high voltages (50-2000 V) in molecular plating.⁸

A general procedure for molecular deposition is as follows: A solution is prepared of either hydrochloric or nitric acid (~3N) at a concentration of 10 mg/mL of the solute to be deposited. Anywhere between 25 to 250 mL is added to 10 mL of iso-propyl alcohol. This is then transferred to an an electrodeposition cell that has the target backing (e.g., thin aluminum) as the cathode and a platinum wire as the anode. The voltage is then applied, and the compound deposits onto the target backing.

Painting produces metal oxide targets by dissolving a metal in a solution of alcohol and lacquer. The solution is applied drop-wise to a target backing which is slowly rotated. The process is complete after the foil is removed from the rotating mount and heated in oxygen, forming a metal oxide film on top of the backing material. This method was first used to produce uranium oxide films on platinum foils by Jorgensen in 1944.⁹ The method has been successfully extended to *d*-transition metals,¹⁰ and was the standard method of actinide target production at Lawrence Livermore National Laboratory from 1969-1978.¹¹

This method has several limitations and has been described as the last option available when "...depositing refractory compounds and for all other sources when all else fails."¹² Painting will lead to a non-uniform metal oxide layer; the target will be thinner in the middle and thicker at the edges. It can not be used to make thick targets (>500 μ g/cm²), because the metal oxide will crack and flake off the substrate's surface.

The Polymer-Assisted Deposition (PAD) method was first described by Jia *et al.* in 2004.¹³ The PAD method shares many similarities with the painting method of target production but was invented independently. In the PAD method, a metal chloride is dissolved in an aqueous solution of a multi-dentate polymer. The coordinating nature of the polymer helps dissolve a greater amount of the metal chloride than would be possible in a generic lacquer, see Figure 1.4. The solution is spin coated onto an atomically smooth surface (root mean surface height deviation ~1 nm). The resulting metal-organic film is heated in an oven to temperatures greater than 600 °C in air. The organic part of the metal-organic film depolymerizes and is removed by evaporation. The metal that is left on the surface is converted to a metal oxide by this process. The PAD method produces metal oxide films several orders of magnitude more homogenous

than comparable methods discussed above.

The metal-organic solutions are the key to why the method works well. The polymer used for this work was polyethylenimine (PEI). The organic molecule chelates to the dissolved metal, this forms the metal-organic covalent complex, presumably through the interaction of the lonepair of electrons on nitrogen to the metal cations, see Figure 1.4. An advantage of the method is that the solutions are all aqueous and thus do not involve volatile or hazardous organic solvents.



Figure 1.4 Putative structures of PEI complexed to a metal cation.

The viscosity of the solution can be adjusted by the addition or removal of water. The resulting metal-organic solutions are then spin-coated onto the substrate or target backing of interest.

The next step of the method is the thermal decomposition of the polymer after spin coating. During the thermal decomposition process the organic constituents of the film decompose and the surface is left with only a metal surface that quickly forms an oxide as it is heated in an oven in air. The surfaces created with the PAD method have been shown to be highly homogeneous, and studies of the film thickness as a function of the calcination temperature have shown that at ~500 °C only the metal oxide layer is left on the surface while any carbon, nitrogen, or hydrogen atoms are no longer present; which has only been seen for d-and f-transition metals.⁷

1.3 Techniques and Instruments of Transactinide Gas-Phase Chemistry

The transactinide elements have an atomic number (Z) greater than 103, and are comprised mostly of the fourth row d-transition metals. As heavy transition metals, they are predicted to have low volatility and high atomic melting points, much greater than 1000 °C. However, there are some inorganic compounds (*i.e.*, chlorides and bromides) that should have appreciable volatility and lower melting points, allowing for the study of their chemistry in the gas-phase.

The generalized method for studying such complexes in the gas-phase is as follows: 1) After irradiation of the target material with the appropriately selected heavy-ion the element is separated from the beam by the use of a velocity separator or a magnetic rigidity separator like the Berkeley Gas-filled Separator (BGS, chapter 5); the atoms are then stopped in the gas-phase in a chamber filled with a gas at a pressure that ensures all the atoms will reach the end of their range within it, this chamber is called a Recoil Transport Chamber (RTC) and is typically separated from the separator by a thin Mylar window. 2) In the RTC a complexing chemical agent is introduced into the gas in order to cause a chemical reaction with the atoms that have been stopped; from the RTC the new chemical compounds are studied by various chromatography methods, discussed in more detail later. 3) After chromatography of the new compound it is necessary to cluster it on aerosol particles and place it in front of detectors in order to measure the yield from the decay of the radionuclide. There are two types of gas-phase chromatography performed with transactinides, thermochromatography and isothermal chromatography. Thermochromatography has a variable temperature profile for the column while isothermal chromatography has a constant temperature, Figure 1.5. Thermochromatography is ideal for compounds that have their volatility within the narrow range of temperatures that permit semiconductor detectors to operate, that is because the method often uses semiconductor detectors as the column material for chromatography. Isothermal chromatography is ideal for chemical compounds that are volatile at temperatures above the operating temperatures of semiconductor detectors, but a drawback is they often require more data to obtain physical meaning because data needs to be taken over several temperatures and only one temperature can be explored per experiment; isothermal chromatography will be the focus of all further discussions on transactinide chemistry in this thesis.



Figure 1.5 Left: Basic principles of thermochromatography. Right: Basic principles of isothermal gas chromatography. From Türler *et al.*¹⁴

The first experiments studying gas-phase transactinides were performed by Zvara and coworkers at Dubna.^{15,16,17} In these experiments, the atoms of interest were not separated from the beam or fission fragments and the thermochromatographic column was connected directly to the the RTC. Now it is more common to couple a gas-jet transport system from the RTC to the chromatographic system because this acts as a chemical method to separate non-volatile compounds from the volatile transactinides of interest.¹⁸

The goal of gas-phase chemists has been to study these volatile chemical compounds in the gas-phase and in order to do this the On-Line Gas Chromatography Apparatus (OLGA II) was made at GSI and serves as an illustrative example of how these experiments are performed. OLGA II was designed to "...continuously separate volatile products and to collect them by deposition in a detection system."¹⁹ The OLGA II system starts as follows: 1) Recoiling nuclei are embedded onto potassium chloride aerosol particles in the gas-phase. 2) The aerosols are stopped in a quartz wool plug. 3) HBr or other strong halogenating gas is passed over the glass quartz wool plug which is heated to 900 °C. 4) The volatilized metal complex was then passed into a variable oven for chromatography studies. 5) After chromatography the products are embedded onto aerosols again and passed to a tape detector counting system. Figure 1.6



Figure 1.6 Schematic of OLGA II. (Gäggeler 1991)

1.4 Rutherfordium Gas-Phase Chemistry

Relativistic effects starts to play a dominant role in the chemistry of elements as early into the periodic table as mercury and gold, and can completely dominate the chemistry of transactinides-- the reason for their influence is described herein. Since the atomic number (Z) for each consecutive element increases, as one goes to heavier elements the core electrons within these elements move faster due to the presence of a larger positive nuclear charge. This has the effect of increasing the mass of the inner electrons and this mass increase is expressed in the following equation,

$$m = m_0 \sqrt{(1 - \frac{v^2}{c})}$$
 (1.8)

Here m_0 is the rest mass of the electron, v is the speed of that electron, c is the speed of light and m is the new value of the mass. Relativistic effects also change the average distance an electron is from the nucleus, this is given by the effective Bohr radius equation,

$$a_B = a_B^0 \sqrt{(1 - \frac{v^2}{c})}$$
(1.9)

Here a_{B}^{0} is the normal Bohr radius of an electron in an atom, and a_{B} is the effective Bohr radius. The primary effect of relativistic effects is to bring the s and $p_{1/2}$ -electrons closer to the nucleus, and thus lower their energy. This has the secondary effect of screening the nuclear charge from the other electrons, namely those in $p_{3/2}$, d, and f-orbitals, and thus raising their energy.

Originally it was thought that rutherfordium would behave like a p-block metal. Because

relativistic effects were known to lower the energy for $p_{1/2}$ orbitals and raise the energy of dorbitals, the predicted electronic structure of rutherfordium was calculated to be dominantly described by [Rn]5f¹⁴7s²7p².^{20,21,22,23} After unsuccessful attempts were made to look for volatile atomic rutherfordium behavior,²⁴ a typical lead-like property, and after more refined calculations²⁵ showed that rutherfordium's electron configuration should be [Rn]5f¹⁴6d²7s², it is no longer thought that rutherfordium behaves like a p-block metal.²⁶

In the 1990s rutherfordium was reacted with chlorinating²⁷ and brominating²⁸ agents to make rutherfordium (IV) chloride and rutherfordium (IV) bromide, respectively. Rutherfordium (IV) chloride was of special interest to transactinide chemists because it was not known if it would be more or less volatile than its homologue, hafnium (IV) chloride. Hafnium (IV) chloride is less volatile than zirconium IV chloride and from extrapolating this trend, it was predicted that rutherfordium (IV) chloride would be the least volatile in this series.²⁹ Also non-relativistic calculations made a similar prediction.³⁰ However, relativistic calculations predicted that rutherfordium (IV) chloride would be more volatile than hafnium (IV) chloride, see Figure 1.7.^{31,32}



Figure 1.7 Volatility of zirconium (IV) chloride, hafnium (IV) chloride, non-relativistic

rutherfordium (IV) chloride (nr), and relativistic rutherfordium (IV) chloride (rel).³³

The experiments with rutherfordium (IV) chloride established that rutherfordium (IV) chloride is more volatile than hafnium (IV) chloride, confirming the role relativistic effects play in transactinide chemistry.^{34,35,36} The homolog bromide series for group 4 metals showed that rutherfordium (IV) bromide has a similar trend in volatility.^{37,38} From those data it is possible to perform a Monte Carlo fit to determine the adsorption enthalpies on quartz (the material of the chromatographic coloumn) of both rutherfordium (IV) bromide and rutherfordium (IV) chloride, see Figure 1.8 and ref[³⁹] for more details on how these calculations are performed.



Figure 1.8 Adsorption enthalpies for group IV metal chlorides and bromides.⁴⁰

Another physiochemical property, the heat of sublimation, can be estimated. A linear correlation exists between the heat of adsorption on quartz for a volatile compound and its heat of sublimation. Thus by studying this behavior for a large set of compounds, a reliable estimate of the heat of sublimation can be made.⁴¹,⁴²

A problem that often arises when studying rutherfordium chemistry is its tendency to form oxy halide compounds (RfOCl₂). As oxy halide metal compounds are less volatile than pure halide metal compounds,⁴³ much care has to be taken to assure that oxygen does not contaminate these experiments. When RfOCl₂ and HfOCl2 were studied, it was found that they have comparable behavior, thus the effects of relativistic effects would have been less obvious.⁴⁴

1.5.1 Production of Long-Lived Rutherfordium: ²⁶¹Rf

There are several isotopes of rutherfordium that have a half-life that is long enough to perform chemistry: *i.e.*, ²⁵⁹Rf ($t_{1/2} = 2.5$ s), ²⁵⁷Rf ($t_{1/2} = 4$ s), ²⁵⁵Rf ($t_{1/2} = 1.5$ s). However, working with isotopes that decay so quickly is not easy; working with isotopes that have half-lives of minutes is preferable. Rutherfordium-261 with a half-life of 75 s is the perfect candidate to explore the chemistry of rutherfordium.

In 1970 Albert Ghiorso and coworkers were the first to synthesize rutherfordium-261.⁴⁵ The nuclear reaction they studied was ²⁴⁸Cm(¹⁸O, *5n*)²⁶¹Rf. They observed a broad alpha peak from 8.2-8.3 MeV. The broadness in the peak is presumably from the 8.22 MeV alpha-particle from ²⁵⁷No and an 8.28 MeV alpha-particle from ²⁶¹Rf. Their measured cross section is 5 nb for a laboratory bombarding energy of 97 MeV. In the same year, Robert Silva and colleagues in collaboration with Ghiorso's team eluted ²⁶¹Rf from a cation exchange resin in the presence of tetravalent zirconium and hafnium, and trivalent actinide tracers.⁴⁶ At the time it was not known whether rutherfordium would behave like a group 4 metal or would follow the actinide series in its chemistry. The results of this experiment showed that 261Rf eluted with the tetravalent hafnium and zirconium tracers and solidified its place as a group 4 metal.

In 1995 ,Kadkhodyan et al. also synthesized ²⁶¹Rf via ²⁴⁸Cm(¹⁸O,5n)²⁶¹Rf reaction.⁴⁷ The

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authors measured a half-life of 79 s. In 2000 Sylwester *et al.* using the same nuclear reaction were able to refine this half-life to 75 s by obtaining better statistics.⁴⁸ Other authors that have investigated ²⁶¹Rf production are Lazarev *et al.* in 2000 from the nuclear reaction ²⁴⁴Pu(²⁵Ne, 5n)²⁶¹Rf.⁴⁹ Finally the work presented in this thesis discusses the production of ²⁶¹Rf using the nuclear reaction ²³⁸U(²⁶Mg, 3n)²⁶¹Rf.

Chapter 2: Polymer-Assisted Deposition

2.1 Introduction

The preparation of homogenous metal oxide films (100 to750 nm) is of interest to nuclear science for use as targets in nuclear reactions. Metal oxide targets, prepared for nuclear science applications, are conventionally made by molecular plating.^{50,51} However, this method suffers from poor adhesion to the backing material and lacks homogeneity at target thicknesses less than about 300 nm.⁵² Jia *et al.* recently reported an alternative method, polymer-assisted deposition(PAD),⁵³ for producing crack-free homogenous metal oxide films with uniform thicknesses between 20 and 400 nm.⁵⁴,⁵⁵ In the PAD method, a water-soluble multidentate polymer binds to metal precursors resulting in a homogenous distribution of the metal in solution. The solution is spin coated and then annealed to yield a high-quality metal oxide film. In this thesis, metal oxide films prepared by PAD were created as an alternative method of target production.

Targets composed of actinide oxides are necessary to synthesize the relatively long-lived and neutron-rich isotopes of transactinides (Z>103). The PAD method was used to study the oxide films of europium (Eu) and thulium (Tm) as models for actinides with an oxidation state of +3 (*e.g.*, americium and curium). Hafnium (Hf) was used as a model of +4 actinides(*e.g.*, uranium and plutonium). The metal oxide film thickness was determined as a function of the weight percent of the metal in solution. The reapplication of the PAD technique on an existing metal oxide layer to build thicker high-quality films was also investigated.

2.2.1 Solution Preparation

All solutions were composed of 15% polyethylenimine (PEI) by weight, with varying

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weight percentages of metal chlorides. PEI (10 kDa, Aldrich) was dissolved in water and adjusted to a pH between 6 and 6.5 using 37% HCl and a pH meter with attached combination pH electrode (Model 231, Orion Research). Solutions were mixed using a vortex mixer, followed by stirring on a magnetic stir plate. Depending on the desired thickness of an appropriate weight percent of europium(III) chloride hexahydrate (99.99%, Aldrich), thulium(III) chloride hexahydrate (99.999+%, MV Laboratories), or hafnium(IV) chloride hexahydrate (98%, Aldrich) was added to the dissolved polymer. All solutions were prepared in a non-clean room environment and were stirred for at least 1 h before use.

2.2.2 Caution

Hafnium(IV) chloride (CAS# 013499053) is highly volatile and a strong irritant. Handling should be limited to ventilated environments.

2.2.3 Single Layered Metal-Organic Films

Silicon [100] wafers (WaferNet) were cut into rectangles (2.00 cm by 0.85 cm). These cut wafers were placed individually into a spin-coater, and 100 µL of the appropriate solution was evenly distributed onto the surface by pipette. The wafers were accelerated for 11 s to a maximum angular velocity of 1500 rpm and spun for 3.0 min in air to form a layer of metal-organic polymer. The angular acceleration was the same between trials; an image of the spin-coater is shown in Figure 2.1. The surface of each sample was scratched three times down to the silicon with sharp tweezers to determine film height. Samples were placed in a muffle oven. The temperature was increased by 50 °C every 15 min from 50 °C to 900 °C. After 15 min at 900 °C, the oven was turned off and allowed to cool to room temperature for several hours.



Figure 2.1 An image of the spin-coater device is shown. Samples were mounted onto a pc fan that served as the spin-coater.

2.2.4 Multiple layered metal-organic films (Reapplication)

Three circular silicon [100] wafers (WaferNet) with diameters of 10 cm were used to test the viability of forming thicker hafnium(IV) oxide films by reapplication of the PAD method. One aliquot of 3.0 mL from a solution composed of 10% Hf and 15% PEI was evenly distributed onto each wafer surface. The wafers were accelerated to a maximum angular velocity of 2500 rpm and spun for 3.0 min in air to form a layer of metal-organic polymer. The metalorganic coated wafers were annealed in the same manner as described above, and the entire process was repeated six times.

2.2.5 Experimental Method – Film Thickness and Visual Assessment

The height of a single layered metal oxide film was determined by using a profilometer (Dektak 150, Veeco) to scan perpendicular to a scratch. Average film thicknesses were measured from three samples spun identically with the same solution. Each sample had three scratches and each scratch was scanned three times at different locations. A plain silicon wafer was scratched similarly to the samples described above, and the tweezers left no measurable indentation into the silicon surface. Outliers were Q-tested out of the data set at 90% confidence. The thickness of the multiple layered metal oxide films were determined by weight, because scratching and scanning by profilometry would have introduced an inhomogeneous surface for the spin coating of consecutive layers. A cartoon of how profilometry works is shown in Figure 2.2. A profilometer works similarly to an older 19th century technology known as a phonograph. A stylus, in this case diamond, is moved in contact with the surface of the sample at a specified force. The profilometer can measure vertical displacements from 10 nm to 1 mm. Thus the profilometer can quantitate the roughness of a surface, but in these experiments it was used to measure the height of the metal oxide film. A sample plot from the profilometer scanning over a scratch is shown in Figure 2.3; the film thickness for a sample is determined by subtracting the flat region of the plot (corresponding to the top of the film) from the bottom flat region (corresponding to the surface of the silicon substrate/backing); the large sharp peak on the right hand region is of a surface anonymity at that location of the film scanned, possibly a comet.

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Profilometer

Figure 2.2 Shown is a cartoon of how profilometry works. Samples are places onto a sample stage and a stylus is passed over the sample. This allows us to measure the film height of a sample.


Figure 2.3 A screen shot of the program that was used with the profilometer. The black region plots the height of the film perpendicular to a scratch, the y-axis is in units of Angstroms and the x-axis is in micrometers. The left hand side of the image displays some parameter values that the instrument was using.

Mounted on the profilometer is an optical camera that can be used to take pictures of the surface of the samples. A picture of one of the samples showing a scratch placed onto the surface in order to determine film height is shown in Figure 2.4



Figure 2.4 An optical image of one of the samples taken with a camera mounted onto the profilometer. The image shows the surface with a scratch that we placed onto the sample.

A scanning electron microscope (SEM) (Ultra 55VP Fesem, Zeiss) was used to determine surface homogeneity on the 200 nm to 200 μ m scale by imaging the surface and the crosssection. An atomic force microscope (AFM) (MFP 3D, Asylum Research) was used to obtain a high resolution image of a 1 μ m × 1 μ m representative section of the surface. The AFM used cantilevers with a spring constant of 3 N/m (Multi75, Budget Sensors) for imaging in the attractive regime in AC mode. The crystal structure of the film created from the reapplication of PAD was determined with an X-ray Diffraction machine (Diffraktometer D500/501, Siemens). The wafer was scanned using 2 θ values of 20 to 66° in 0.05 degree increments at one second per step.

2.3.1 Single Layered Metal-Organic Films

The thickness of the metal oxide film produced by the polymer-assisted deposition method is a function of several variables: angular acceleration of the spin-coater, viscosity of the solution, metal ion concentration, maximum velocity of the spin-coater, total time spun, and the annealing temperature profile.⁵⁶ To determine the optimum conditions for the PAD method, a systematic study was performed studying the effect that varying metal ion concentration has on film thickness for Eu(III), Tm(III), and Hf(IV).

The a-priori expectation of a linear relationship between film thickness and metal ion concentration was not observed, as seen in Figures 2.5-2.7. Spin coating yields film heights having an $\eta^{1/3}$ dependence,⁵⁷ where η is the viscosity. It is hypothesized that the deviation from linearity is due to the increase in viscosity from increasing metal ion weight percent in solution while fixing the polymer weight percent at 15%, thus decreasing the total amount of water available for solvation. Attempts at preparing solutions above 8% Eu, 10% Tm, and 12.9% Hf, all in 15% PEI, were unsuccessful due to a precipitation that could not be re-dissolved. For hafnium, the highest quality film was produced with the 10% by weight (b.w.) Hf solution. Likewise, 6% (b.w.) Eu and 8% (b.w.) Tm yielded the best results for those elements. The standard deviation for each sample was found to be less than 13% of its film height except for those derived from the 8% (b.w.) Eu solution, and the 2% (b.w.) metal ion solutions. The 8%-Eu film appeared inhomogeneous by SEM analysis, and consisted of micro-scale amorphous structures of Eu₂O₃. The 2%-metal ion solutions yielded films with a standard deviation of about 10 nm, which are similar to those produced by the more concentrated metal ion solutions.

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Figure 2.5 Film thickness as a function of metal ion concentration of europium(III) oxide. Error bars correspond to one standard deviation. Error for all solution preparations are negligible

(< 0.05%).



Figure 2.6 Film thickness as a function of metal ion concentration of hafnium(IV) oxide. Error bars correspond to one standard deviation. Error for all solution preparations are negligible

(< 0.05%).



Figure 2.7 Film thickness as a function of metal ion concentration of thulium(III) oxide. Error bars correspond to one standard deviation.

Surface SEM and cross-section SEM images of europium, thulium, and hafnium are shown in Figure 2.8a-c. The surface of 6% Eu and 8% Tm were homogenous with an even distribution of metal oxide grains. However, there was a random distribution of surface aggregates of $2-5 \mu m$ in length in the 8%-Tm films, likely caused by being near the saturation point of Tm/PEI in water. The 10% Hf had the most homogenous surface of all the metals, although some minor surface aggregates are apparent as shown in Figure 2.8c. The cross sections for all metals, Figure 2.8a–c, show highly uniform films. AFM images of the metal oxide films show that the surfaces are composed of grains.



Figure 2.8 (a) Europium(III) oxide film (produced from a 6% by weight europium solution); (b) thulium(III) oxide film (produced from a 8% by weight thulium solution); (c) hafnium(IV) oxide film (produced from a 10% by weight hafnium solution.).

The largest grains occur in the Eu_2O_3 films (30–40 nm in diameter) and the smallest in the HfO₂ films (10–15 nm in diameter). The AFM images confirm the surface homogeneity and uniformity of all the films as shown in Figure 2.9. AFM and profilometry data verify that hafnium forms the most highly uniform and homogenous metal oxide film when SiO₂/Si is used as the backing material. The roughness, as measured by AFM, has a root mean square, rms, of 7.46 nm, 1.87 nm, and 1.45 nm for europium, thulium, and hafnium films, respectively, over $1 \,\mu\text{m}^2$.



Figure 2.9 AFM images of metal oxide films after single application of the PAD method: (a) europium(III) oxide film produced from a 6% by weight europium solution, (b) thulium(III) oxide film produced by an 8% by weight thulium solution, and (c) hafnium(IV) oxide film produced from a 10% by weight hafnium solution.

2.3.2 Multiple Layered Metal-Organic Films (Reapplication)

The PAD method was applied to an already formed metal oxide layer to create thicker targets than were possible by spinning a concentrated metal ion solution only once. Due to the large size of the wafers, it was necessary to spin at an angular velocity of 2500 rpm to minimize comets and to form a uniform layer over the entire surface. The process resulted in multi-layered films of HfO_2 with an average final height of 598 nm. Uniform film thickness across the width of the wafer was confirmed by imaging several locations by cross-section SEM. The change in height of hafnium(IV) oxide after each interval is summarized in Figure 2.10.



Figure 2.10 The graph shows the cumulative height of hafnium(IV) oxide after reapplication of the PAD method. The experiment was done in triplicate and the results averaged, except layer 6 which was done in duplicate. Uncertainty from the analytical balance translates to ± 2 nm.

Film thickness increased by 99 nm (\pm 2 nm) after each interval step. The upper limit of the method toward reapplication was not determined. Surprisingly, no striations were seen from a cross-section SEM (Figure 2.11) of the final wafer, indicating uniform growth.



Figure 2.11 Left: Representative surface SEM of a hafnium oxide film produced from reapplication of the PAD method using a 10% by weight hafnium solution. Right: Representative cross-section SEM of the same hafnium(IV) oxide film.

An AFM image (Figure 2.12) of the film shows that the surface is composed of grains between

15 and 20 nm in diameter with a roughness rms of 2.35 nm over 1 μ m².



Figure 2.12 AFM image of a hafnium oxide film produced from reapplication of the PAD method using a 10% by weight hafnium solution.

X-ray Diffraction (XRD) analysis was conducted on the multi-layered HfO₂ film and compared with HfO₂ powder produced from baking several milliliters of a 9% (b.w.) Hf solution in a glass vial at 900 °C until a white powder formed. Figure 2.13 shows the close correlation between the HfO₂ film XRD pattern and the HfO₂ powder XRD pattern for polycrystalline HfO₂. The most intense peaks from the HfO₂ film are at 28.4°, 31.7°, 34.4°, 35.6°, and 55.8°. This agrees well with the library XRD pattern of simple monoclinic HfO₂ (PDF# 34-0104). The sharp peak at 33.1° is likely caused by the silicon backing. The relative intensities of the powder HfO₂ XRD pattern and the HfO₂ library XRD pattern were similar as seen in Figure 2.13a. However, differences in relative intensities in the HfO₂ film XRD pattern versus the HfO₂ powder XRD pattern were observed. This is likely due to the HfO₂ powder having a random distribution of lattice planes while the HfO2 film has preferred orientations which skew the peaks. The broad widths of the peaks imply small grain sizes⁵⁸ in agreement with AFM and SEM analysis.



Figure 2.13 a.) X-ray Diffraction pattern of HfO_2 powder. b.) X-ray Diffraction pattern of a multi-layered film of HfO_2 on Si [100]. Below each XRD pattern is the relative intensities for

simple monoclinic HfO_2 .

2.4 Advantages of Polymer-Assisted Deposition

Molecular plating has been used by Trautmann et al.⁵⁹ and Mullen et al.⁶⁰ to create uranium, plutonium and curium oxide films. Their films ranged from 150 to 550 nm in thickness, which are typical for nuclear science applications. We have independently shown that the PAD method can produce films in a wider range of thicknesses than molecular plating. In addition, an advantage of using PAD is that it produces highly uniform and homogenous metal oxide films below 300 nm, while molecular plating method suffers in this region. A second advantage of the PAD method is that it can be reapplied to create thicker films without losing uniformity. A disadvantage of the PAD method is that the coating efficiency for a single application is ~ 33%. However, the solution that did not adhere to the surface can be collected and reused resulting in minimal loss of a precious metal, with the overall deposition efficiency approaching 100%. Molecular plating has ~ 90% efficiency for the deposition of metal out of solution and comparable to PAD.^{61,62} Thus, the PAD method is likely a robust route to create metal oxide films suitable for nuclear science applications which require film uniformity and controlled film thickness.

It should be noted that the potential for silicon diffusion into the metal oxide films was not investigated, because this would not affect the overall energy loss of a high-energy beam passing through a metal oxide film and substrate. Future work will study the mechanical properties of metal oxide films of uranium, plutonium and curium created by the PAD method, before and after high intensity heavy-ion irradiation.

2.5 Development of Radioactive Spin Coating Methods

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The process of spin coating applies a thin film of liquid evenly over a surface and is a crucial step in preparing targets by the PAD method. It is accomplished by utilizing centripetal force produced by rotating at angular velocities between 500 and 3000 rpm. Spin coating is used in many areas of technology, including fabrication of microcircuits, magnetic disks, compact disks, digital display devices, and other materials. The containment and recovery of the spin-coated solutions is not a common practice, and will be necessary when preparing radioactive targets by the PAD method. Prior designs for sealed spin-coating apparatuses are usually bulky and often require the use of vacuum pumps. Herein we show the design of a radioactive spin coating apparatus that is chemically inert and self contained.

Our radioactive spin coater design features a cylindrical sample-containment compartment made of poly(aryl- ether-ether)ketone (PEEK). A rectangular mount sits at the bottom of the compartment; it serves to hold the sample wafer in place while the apparatus is in use. A screw-on cap designed to fit snugly around the compartment, together with an o-ring of Viton® positioned at the outer rim of the cylindrical unit, ensure an air-tight seal and prevents leakage of the spin-coating solution when the spin coater operates at high rotations per minute. This compartment is attached to a 3-volt DC motor, which is connected to a variable voltage power supply. The DC motor's angular velocity dependence on the voltage setting of power supply is shown in Figure 2.14. The motor creates the rotating motion required to distribute the solute evenly.

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Figure 2.14 Angular velocity dependence on foltage of spin coater

The thickness of the film produced by spin coating is dependent on several variables including angular acceleration, speed of the rotation, air flow above the spin-coater, and the concentration and viscosity of the liquid used. A way to characterize a functional spin-coater is to observe a relationship between the concentration of the solution and the thickness of the film applied. In the particular case of the radioactive spin-coater characterization, the following procedure was used.

Polystyrene (MW: 350.00) was dissolved in toluene to prepare seven solutions with concentrations shown in Table 2.1. Glass wafers (1.85 cm x 0.85 cm x 1.2 mm) were rinsed briefly in acetone and dried with compressed air to clean dust and other contaminants from the surface. After being placed on the mount, 0.1 mL of a polystyrene solution was added to the top of a glass slide with an automatic pipette.

Series	Volume of Solution	Concentration	Calculated
No.	Added (µL)	(g/100mL)	Thickness (nm)
1	100	2.858	221.48
2	100	5.424	523.95
3	100	7.991	981.97
4	100	10.777	1959.28
5	100	13.337	2173.11
6	100	15.983	3743.99
7	100	18.808	5475.11

Table 2.1. Thickness of polystyrene films at various concentrations without cap

Once the solution was added in small aliquots to the glass slide , the spin-coater was switched on and set to rotate at $2,790\pm50$ rpm. The samples were spun for 3 minutes each. They were then removed from the spin-coater and their thicknesses were measured by a UV-Vis spectrometer. Equation 2.1 and 2.2 were used to determine the thickness from spectral data. The calculation results are presented in Table 2.2.

$$\nu = \frac{\frac{n(\lambda_1)}{\lambda_1} - \frac{n(\lambda_2)}{\lambda_2}}{N_{cuc}}$$
(2.1)

$$d = \frac{1}{2\nu}$$
 (2.2)

Constants $n(\lambda_1)$ and $n(\lambda_2)$ are the refractive indices at their corresponding wavelengths; the value of 1.6 was used for polystyrene of both molecular weights. N_{cyc} is the number of cycles in the interference fringes between wavelengths λ_1 and λ_2 . For data consistency, λ_1 and λ_2 are chosen to cover the range that contains minimal noise interference (~360-790 nm). Finally, d represents the thickness of the film calculated. Wavelength range in the interpretation of UV-Vis

data is limited to between 350-1000 nm because glass has a strong absorption at wavelengths below 300 nm. A sample UV-Vis spectrum is shown below in Figure 2.15.



Figure 2.15. A representative UV-Vis spectrum of polystyrene film at 13 g / 100 mL.

By measuring film thicknesses of various polystyrene concentrations using a UV-Vis spectrometer, an exponential relationship is observed. Graph of concentration versus thickness is shown in Figure 2.16.

In order to ensure that the container and lid assembly would not leak, a highly fluorescent die (Rhodamine B) was spin coated. The same steps were repeated using 0.1 M of Rhodamine B solution. Its vibrant color and UV fluorescence allow an easy detection of any leak were it to occur during the procedure. By visual inspection, it is reasonable to conclude that no leak took place during the operation of the spin coater, both with and without the cap. All of the liquid was contained within the PEEK device and none was found to have been slung out into the chemistry

hood and surrounding lab benches.



Figure 2.16 Film thickness vs. solution concentration with the cap off.

To ensure that the radioactive spin-coater will perform adequately even with an air-tight seal, the same procedure was executed with the cap on. Selected concentrations of polystyrene (MW: 350.00) dissolved in toluene were spun on glass slides. The experimental set up was the same as described previously, all except the cap was screwed on to produce an air-tight seal. In addition, the spin coater was set to operate for 1 minute at 1000 rpm. The film thickness and concentration of the corresponding solution demonstrate an exponential relationship. The numerical data and graph are shown in Table 2.3 and Figure 2.17. This result demonstrates that the cap allows the radioactive spin-coater to contain the solution used without compromising the quality of the film produced.

Series	Volume of Solution	Concentration	Calculated
No.	Added (µL)	(g/100mL)	Thickness (nm)
1	100	10.777	1239.401897
2	100	13.337	1725.05603
3	100	15.983	2779.263195
4	100	18.808	4541.995192

Table 2.3 Thickness of Polystyrene films at various concentrations with cap.



Figure 2.17 Film thickness vs. solution concentration with the cap on.

The mount size inside the spin-coater can be modified to fit individual needs. The current design accommodates rectangular glass slides with the dimension 1.00 cm x 2.90 cm, see Figure 2.18. With proper alteration, the apparatus can be used to spin coat wafers of various shapes and sizes. In addition, the height of the mount and the well volume can be adjusted to accommodate various experimental designs. The angular velocity of the radioactive spin-coater can be varied by adjusting the voltage setting on a power supply connected to the motor.



Figure 2.18 Images of the radioactive spin-coater.

The original intent of the design of a radioactive spin coating apparatus was to improve methods of nuclear target production. However, the radioactive spin-coater can also be a valuable asset in creating films from other hazardous or expensive solutions.

2.6 Conclusion

Europium, thulium and hafnium oxide films were annealed onto silicon substrates using polymer-assisted deposition. The films were characterized by SEM, AFM and profilometery. The characterizations showed that the films were crack free, uniform, and homogenous. Advantages of PAD over molecular plating include that it produces high-quality thin films below 300 nm in thickness and that reapplication of the method creates thicker metal oxide films of equal quality.

Chapter 3: Irradiation of Polymer-Assisted Deposition Targets

3.1 Introduction

The purpose of this chapter is to describe our experiments of irradiating targets made by the Polymer-Assisted Deposition (PAD) method. A modified procedure was used for the manufacturing of these targets than that described in chapter 2. The modification was the use of silicon nitride backing instead of the pure silicon that we used previously. The reason for the change is because silicon nitride can be made to be as thin as 100 nm but silicon can not be thinned to that thickness over a large area. The results from heavy-ion irradiation of several metal oxide targets, prepared by the PAD method on silicon nitride backings, at the 88-in Cyclotron of the Lawrence Berkeley National Laboratory (LBNL) will be discussed. Characterizations of the targets after irradiation were performed by scanning electron microscopy (SEM) and atomic force microscopy (AFM). Target integrity during irradiation was monitored by Rutherford scattering as a function of time.

3.2.1 Target Manufacturing

The metal oxide targets were prepared as follows. A low-pressure chemical vapor deposition (LPCVD) furnace (tystar, TYTAN) was used to epitaxially grow low-stress silicon nitride (Si₃N₄) onto both sides of 4-in single-sided polished (SSP) silicon wafers [1 0 0]. Dichlorosilane and ammonia with flow rates of 100 and 25 sccm, respectively, were used as the silicon nitrating source at 18.7 Pa and 835 °C. The film stress was about 200 MPa and the deposition rate was 40 Å/min. The Si₃N₄ film was produced to yield 1000±20 nm (344±7 μ g/cm²) before etching. Four rectangles (1.8×1.3 cm) were scratched through the Si_3N_4 layer, on the unpolished (bottom) side of the silicon wafers, to expose the silicon surface. These patterned wafers were then placed for 8–10 h in a 20% potassium hydroxide bath at 80 °C, to etch away the silicon and leave only a rectangular surface of Si_3N_4 , a scheme is shown in Figure 3.1.



Figure 3.1 The process of making silicon nitride backings.

3.2.2 Solution Preparation

A solution of 8% by weight (b.w.) thulium with 15% (b.w.) polyethylenimine (PEI) in water was prepared exactly as previously described in chapter 2. A 3 mL aliquot of the thulium solution was spread on top of wafers containing the four Si_3N_4 windows. The wafers were spun at 1500 rpm and then baked over a period of 3 h in a muffle oven to a final temperature of 600 °C. The process creates a thin layer of thulium(III) oxide (Tm_2O_3), while the polymer decomposes to volatile oxides. A second layer of Tm_2O_3 was coated on the wafer by adding an additional 3 mL aliquot of the 8% (b.w.) thulium solution and repeating the steps described above. The final thickness of the Tm_2O_3 film was ~250 nm (~220 µg/cm²) as measured from taking the average of several cross-section images by SEM. The wafers were scribed and broken into pieces of 7.6×6.0 cm. The outer silicon was used as a frame to support the metal oxide film and silicon nitride window on a target ladder for heavy-ion irradiation.

3.2.3 Irradiation Conditions

Two Tm_2O_3 targets were each irradiated separately with a different heavy-ion beam of either 208 MeV Argon (⁴⁰Ar¹⁰⁺), or 180 MeV Argon (⁴⁰Ar⁸⁺). The first target was irradiated with the Ar¹⁰⁺ beam for 35 min at a beam current of 3.1×10^{11} particles/s (50 particle nA) for a total dose of 6.6×10^{14} particles. A second target was irradiated with the Ar⁸⁺ beam for 17 min at a maximum beam current of 1.2×10^{12} particles/s (200 particle nA) for a total dose of 1.3×10^{15} particles. The irradiated targets were easily removed from the target ladder and were subjected to further analysis.

3.3.1 Visual Inspection and Rutherford Scattering

Visual inspection of the Tm_2O_3 target irradiated by the ${}^{40}Ar^{10+}$ beam revealed a slightly darkened rectangular region which is shown in Figure 3.2 but difficult to see. This is hard to see due to the highly transparent nature of targets produced by this method, see Figure 3.3. The dimensions and location of the darkened rectangle are consistent with the known beam spot image after beam collimation. The Tm_2O_3 target irradiated by the higher intensity (200 particle nA) ${}^{40}Ar^{8+}$ beam had a melt spot after irradiation. This was done to test the limits of the method as stationary targets only receive a maximum intensity of ~40 particle nA during an irradiation to prevent melting. The melt spot for the intensely irradiated Tm_2O_3 target indicates an upper-limit of beam intensity that stationary targets prepared by the PAD method can withstand. From monitoring the quantity of Rutherford scattered particles as a function of time, no decrease in intensity for either target was observed; this indicates target flaking did not occur during the irradiation.



Figure 3.2 An irradiated Tm_2O_3 target mounted behind the target ladder is shown in the foreground. A slightly darkened rectangular region can be seen at the top of the silicon nitride that corresponded to the beam spot image. The purple color is the silicon frame used to support the silicon nitride layer. The metallic surface is the aluminum target ladder in which the targets

were mounted. In the background is a non-focused image of the support frame.



Figure 3.3 The same target is shown in Figure 3.2 except the image is focused on the background, highlighting the transparent nature of targets produced by the PAD method. The object shown in the background in the support frame used for the irradiation.

3.3.2 Scanning Electron Microscopy Inspection

An SEM (Ultra 55VP Fesem, Zeiss) with an acceleration voltage of 5 kV was used to determine surface homogeneity of the 40 Ar ${}^{10+}$ -irradiated target at a magnification of 274×. A cross-sectional SEM image was also taken to determine uniformity at a magnification of 31 k×. A representative image of the surface after the irradiation is shown in Figure 3.4a. Small surface aggregates randomly distributed on the surface can be seen, and were present before irradiation. This is likely due to using non-clean room techniques in the application of the PAD method. A

small pinhole ~7×4 µm is also visible in the upper-right-hand side of Figure 3.4a. Pinholes are seen prior to irradiation and are likely due to defects in the substrate, thus the wafers should be cleaned thoroughly before adding silicon nitride to the surface. A representative SEM crosssection of the target after irradiation is shown in Figure 3.4b; two layers of Tm_2O_3 can be clearly seen in the figure. The back edge was tilted ~8° toward the top of the wafer, in order to image the surface of Tm_2O_3 in tandem with viewing the striated Tm_2O_3 layers. The figure shows the high degree of uniformity achieved with the PAD method. It should be noted that the previous experiments described in chapter 2 did not show striations when utilizing the reapplication of the PAD method, this may be due to not baking the silicon nitride targets up to 950 °C but only to 500 °C (silicon nitride surfaces start to decompose near 600 °C). The occurrence of striation is likely dependent on the annealing temperature profile. The SEM analysis of the irradiated target show no significant deviation from those imaged prior to irradiation.

3.3.3 Atomic Force Microscopy Inspection

An AFM (MFP 3D, Asylum Research) was used to obtain a high-resolution image of a $1 \times 1 \ \mu m^2$ representative section of the irradiated target surface and a non-irradiated portion of the same target for 40 Ar¹⁰⁺ irradiation. The AFM used cantilevers with a spring constant of 3 N/m (Multi75, Budget Sensors) for imaging in the attractive regime in the AC mode. The AFM images are shown in Figure 3.5a and b. The homogeneity and granular appearance of the Tm₂O₃ layer on the non-irradiated portion of the target is consistent with previous experiments with a root mean square (RMS) roughness of 1.1 nm. The irradiated portion, Figure 3.5b, also shows a homogeneous surface with low surface variability with an RMS roughness of 2.0 nm.

After irradiation, the homogeneity of the film is only slightly reduced.



Figure 3.4 (a) Representative surface SEM of the irradiated Tm_2O_3 film produced from the PAD method using an 8% by weight Tm solution. (b) Representative cross-section SEM of the same

 $\mathrm{Tm}_2\mathrm{O}_3$ film.



Figure 3.5 (a) Representative AFM of the non-irradiated area of the Tm_2O_3 film produced from

the PAD method, (b) representative AFM of the irradiated area of the Tm_2O_3 film produced by the PAD method.

3.4 Conclusion

From monitoring the Rutherford scattered during irradiation, it was observed that there was no loss of target material. This is in contrast to other methods that may produce targets that flake even before irradiation.⁶³ Loss of target material through the course of a beam irradiation will decrease the overall production of the desired nuclear reaction channel, and may prelude the undesired consequence of contamination if the target is composed of a radioactive isotope. Another consequence of target flaking is the loss of expensive enriched isotopic material. Therefore, the PAD method is an advantageous target methodology for preparing uniform, homogeneous crack-free metal oxides for heavy-ion irradiation. Further experiments are planned to determine the target temperature during irradiation and the optimum thickness of silicon nitride to minimize the energy-transfer from heavy ions, while retaining high structural integrity.

Chapter 4 Design and Testing of Gas-Phase Apparatus

4.1 Introduction

The research objective was to extract radionuclides from the Berkeley Gas-Filled Separator (BGS, discussed in detail in Chapter 5) perform chemistry on them and then measure the yield of the chemical process by monitoring their decay. In order to accomplish this, electronics, gas-jet systems, and detector arrays were designed and constructed. Computer programs were written to control these systems and scripts were written to analyze the data. A schematic of the process is shown in Figure 4.1

From the BGS radioactive atoms of interest were stopped in the gas-phase by the use of the Recoil Transport Chamber (RTC, described in chapter 1), the atoms were transported via a gasjet to the alpha-wheel apparatus that is described in this chapter and the decay was monitored with the electronics, data acquisition systems, and data analysis codes described herein.



Figure 4.1 A cartoon schematic of the hardware constructed for the gas-phase testing experiments that were performed; the results are presented in this chapter.

4.2 The Alpha-Wheel Apparatus

The detectors were housed in the alpha-wheel apparatus. Radionuclides were transported from the BGS via gas-jet that sprayed them onto a rotating sample holder that passed in front of alpha-detectors; the sample holder plus alpha-detectors is called the alpha-wheel apparatus, see Figure 4.2.



Figure 4.2 This is a picture of the alpha-wheel apparatus. There are three of the four alphadetectors positions filled in the device. The sample holder is the beige disk to the right. The cap is made from aluminum and is to the left with the hole for the capillary next to the red arrow..

The lid has a hole in the upper right corner (shown to the left of Figure 4.2 with a red arrow) to fit the capillary. The capillary was composed of Teflon and was the exit of the gas-jet. The gas-jet sprays a small spot onto the sample holder. The location it sprayed on the sample holder is covered in 1 μ m Mylar foil. The radiation emitted from the radionuclides easily passes through the Mylar foil and strikes the detectors in the alpha-wheel apparatus. A figure of the Mylar covered sample holder in the alpha-wheel apparatus is shown in Figure 4.3. Also shown to the left of the figure is the nozzle that leads to a vacuum for exhaust.



Figure 4.3. A picture of the sample holder with the Mylar foil in the alpha-wheel apparatus.

The alpha-wheel utilized semiconductor detectors for the detection of ionizing radiation from alpha-decaying radionuclides. The semiconductors detectors used for this project were solid crystals of silicon. The valency for silicon is 4, and thus forms 4 bonds with other silicon neighboring atoms. Because all of the silicon's electrons are tied into bonding the band-structure of silicon has a filled valence band and an unfilled conduction band. The separation in energy between a material's valence band and conduction band is called the energy gap, and this is what determines whether a material is considered an insulator or a conductor; the band gap for silicon is 1.1 eV. Due to the statistical nature of thermal energy there will be a small number of electrons in the valence band that will have significant energy to cross the energy gap and enter the conduction band. The atom that has lost a covalently bound electron is termed a "hole". An electron from a neighboring atom will be dislodged and will fill the hole. However, this process creates a new hole at the second atom. Thus it will appear as if the hole migrates across a crystal, but it is electron's from neighboring atoms that move. The probability, p(T), that an electron-hole pair is created from thermal fluctuations in a semiconductor crystal is given in Equation 4.1.

$$p(T) = CT^{3/2} e^{-\frac{L_g}{2kT}}$$
(4.1)

where T is the temperature in kelvins, C is a constant of proportionality, k is Boltzmann's constant and Eg is the bandgap energy. The equation shows that the probability density of electron-hole pairs is strongly correlated to temperature; as the temperature decreases the concentration of electron-hole pairs will decrease exponentially. At any given temperature the process of electron-hole production will equal the rate of electron-hole destruction due to recombination; at equilibrium the number of electrons in the conductance band (n_i) will equal the number of holes in the valence band (p_i) .

$$n_i = p_i$$
 (4.2)

The subscript 'i' signifies that the semiconductor crystal is pure and has not been doped.

It is possible in semiconductors to control their electrical conductance by the addition of dopants into the crystal lattice of the semiconductor. Dopants are atoms with a valency different than 4, and often have a valency of either 3 or 5. By adding a dopant of valency 5 (*e.g.* phosphorus, arsenic, antimony) there will be four electrons in the valence band forming covalent bonds, but the fifth electron will be relatively free to travel and will be in a state only slightly beneath the conduction band termed donor states. The type of semiconductor crystal that has been doped with atoms of a valency of 5 or greater is called an n-type semiconductor. In contrast, if an atom of valency 3 or less is used to dope a semiconductor then those dopant atoms won't have enough electrons to form bonds with neighboring silicon atoms. This produces an abundance of holes in the material, and forms acceptor states just above the valence band; this type of crystal is called a p-type semiconductor, shown in figure 4.4.



Figure 4.4 Electronic energy structure for various semiconductor materials.

The velocity (v) of the electrons and holes is governed by the strength of an applied

electrical field (E) and proportional to their respective mobilities (μ).

$$v_h = \mu_h E \tag{4.3}$$

$$v_e = \mu_e E \tag{4.4}$$

However, when an external field is high enough the velocity of the electrons and holes is saturated and are on the typical order of 10^7 cm/s.

The semiconductor crystals are useful in detecting ionizing radiation in the following way. When two semiconductor crystals of different types are brought together, electrons from the n-type semiconductor will diffuse into the p-type material; this continues until the flow of electrons is stopped by the electric field that is from the imbalance of charge, this area of the detector is called the depletion zone. When an ionizing radiation particle enters the depletion zone it creates a series of electron-hole pairs by displacing electrons from their atoms along the trajectory of the particle. Ideally, the ionizing particle should lose all of its energy within the depletion zone of the semiconductor crystal, because the electric field that has been in the depletion region plus the applied voltage will flow electrons in one direction and holes will flow in the opposite direction, shown in Figure 4.5. The charges are collected and converted to voltages using a charge-to-voltage amplifier, and the measured voltage is directly proportional to the energy of the radiation.



Figure 4.5 A cross sectional image of a semiconductor detector with ionizing radiation causing the formation of electron-hole pairs.

As mentioned earlier the depletion zone will naturally have an electric field whose potential (ϕ) is given by equation 4.5

$$\nabla^2 \phi = -\frac{\rho}{\epsilon} \tag{4.5}$$

Where ρ is the charge density and ε the dielectric constant for silicon. The magnitude of the potential is often very near the bandgap of the material. The associated electric field (*E*) can easily be solved for by taking the derivative of the potential along the axis of p-to-n.

$$E(x) = -\frac{d\phi}{dx}$$
(4.6)

As the ionizing particle removes electrons from atoms it will begin to slow down and come to rest. During the slowdown phase the ionizing particle will knock-out electrons imparting
on them a sufficiently high energy that these electrons (termed delta rays) create electron-hole pairs as they decelerate. The average energy the ionizing particle loses to produce a single electron-hole pair is often called the ionization energy and has the symbol ε . The ionization energy is dependent on the kinetic energy of the ionizing particle. The ratio of electrons to holes formed from the energy deposited by the ionizing particle is 1:1, whether the crystal has an ntype or p-type dopant plays no role in the ratio.

The ionization energy is approximately 3 eV for silicon. This is small in contrast to other detector types like a typical gas-filled detector, which requires 30 eV to make an ion pair. As the number of electron-holes will be 10 times greater for silicon than a gas-filled detector this means that the attainable resolution is also greater. However, the ionizing energy is dependent on both the temperature of the silicon and the type of radiation measured. Thus, if you were to measure protons using a calibration from alpha particles the energy value could be off by as much as 2.2%.⁶⁴

As said earlier, the number of electron-hole pairs created by an ionizing particle is directly proportional to the energy of that particle. However, the exact number of electron-hole pairs generated from another ionizing particle of the exact same energy and type will differ slightly. If we plotted the number of electron-hole pairs generated against the energy of the ionizing particles we will see a Gaussian distribution of values. The Gaussian distribution is given as,

$$G(H) = \frac{A}{\sigma(2\pi)^{1/2}} e^{-\frac{(H-H_0)^2}{2\sigma^2}}$$
(4.7)

Here σ is related to the full width at half maximum (FWHM) by FWHM = 2.35 σ , H₀ is the

centroid of the peak, and A is the area of the peak. Thus, we finally have the tools to quantify the observed distribution. It is often considered that the distribution should be due mainly to statistical noise, meaning that it arises from the random fluctuation of events even though the particle may have exactly the same energy and enter the material in essentially the same location. This distribution can be modeled as at the limit of a Poisson process, and the resolution is defined as the FWHM divided by the location of the centroid (H_0), see equation 4.8

$$R|_{Poisson} = \frac{FWHM}{H_0}$$
(4.8)

As the location of the centroid is equal to the number of electron-hole pairs (N) times a proportionality constant (K), and as mentioned earlier the FWHM equals 2.35σ where σ equals $KN^{1/2}$, then equation 4.8 becomes,

$$R|_{Poisson} = \frac{FWHM}{H_0} = \frac{2.35KN^{1/2}}{KN} = \frac{2.35}{N^{1/2}}$$
 (4.9)

As the equation shows, the resolution is determined by the number of electron-hole pairs generated, so as N increases the resolution will increase (R will decrease). However, semiconductor detectors are odd in that the measured resolution is often 3 or 4 times better than that predicted from a statistical analysis. This simply means that the process described earlier for how electron-hole pairs are generated is not independent of each other. This increase in resolution is quantified by a variable called the Fano factor (F), and is related to equation 4.10 as,

$$R|_{Poisson} = 2.35 \left(\frac{F}{N}\right)^{1/2}$$
 (4.10)

For semiconductor crystal detectors the Fano factor (F) will be less than one.

As mentioned earlier these semiconductor crystal detectors often have an external potential applied to them. They will also work when there is no potential applied, but the resolution is greatly diminished. That is because the natural potential that is made across the detector, ~1 V, is not strong enough to sweep the electron-hole pairs to the electronics. Any delay in collecting the ion-pairs will cause a loss of information due to trapping and recombination. Thus, the detector is biased. The bias applied is usually the reverse of that generated naturally by the separation of ions. The p-side of the detector is biased negatively, and the n-side of the detector is biased positively. This ensures that the minor carriers of the n-side (holes) and the p-side (electrons) are attracted across the junction. As the concentration of carriers is so little across the junction the current across the detector is very low. So the entire detector can be thought of as a diode, and as with most diodes if the voltage is increased too much in the opposite direction it will permanently destroy the diode.

4.3 Driving the Stepper Motor

Precise control of the sample holder is crucial in these experiments, as the sample holder is stepped in front of the alpha-detectors. We used a stepper motor (Anaheim Automation, 1SY001S-LW4) to this end. A stepper motor is shown diagrammatically in Figure 4.6.



Figure 4.6 A diagram of the 4-wire stepper motor.

The beginning operation of the stepper motor is to pass current through points A+ to A- (winding A) and from points B+ to B- (winding B). In order to have the motor take a step it is necessary to change the current direction of either winding A or winding B but not both at the same time. An example current switch with an associated step is shown in Figure 4.7.



Figure 4.7 The stepper motor diagram after a current change showing the motor has stepped by 90 degrees.

By changing the direction of the current in the right order it is possible to make the motor rotate clockwise or counterclockwise. In order to do this a circuit was made and is sketched in Figure 4.8. The integrated circuit used to control the switching for V_1 and V_2 was the IC-4049. The logic of the circuit contains 2 bits of information for 4 total combinations: 00, 01, 10, 11. Each of the combinations corresponded to the current in winding A flowing in one direction or the other and similarly for the current flowing in winding B, to cover all possible combinations to make the wheel step. Thus with this simple logic it is possible to control the alpha-wheel apparatus with simple steps by manipulating the voltages sent to the integrated circuit with either 0 V or 5 V logic in order to change the flow of current through the windings. A picture of the final circuit is shown in Figure 4.9.



Figure 4.8 The circuit diagram of the stepper motor driver.



Figure 4.9 This shows the final constructed stepper motor circuit.

4.4 Peak Shaping From the Alpha-Detectors

The Data Acquisition System hardware and software used for the gas-phase experiments sampled voltages at a slow pace, approximately every 10 ms (discussed in more detail also in section 4.5). The pulse rise time which characterizes the signal from the detector is on the order of 10 ns. The 10 ns are due to two causes: The charge transit time, and the plasma time.

The charge transit time is simply the time it takes electron-hole pairs that are generated in the depletion zone to transverse it and be collected. The effects of the charge transit time can be minimized when a large electric field is generated across the detector and when the depletion zone is narrow. Since no electric field is ever homogenous, the migration of the electrons and holes will be a function of its location in the detector and the electric field it feels at that point.⁶⁵

The plasma time is a characteristic for the types of radiation studied later in this chapter, which are alpha particles, but it also a significant component for any heavy charged particles. When an alpha-particles creates ion-pairs along its trajectory, it creates them at such a high density that the electron-hole pairs in the interior of the cloud are shielded from the effects of the electric field. Thus the electron-hole pairs on the outer edge will move first due to the electric field. As the edge ion-pairs migrate the shielding of the interior ions will decrease and they too will start migrating.^{66,67,68,69,70,71,72,73} The time it takes for the plasma to be eroded is termed the plasma time, after which the detector behaves as a normal charge collection process. The amount of time associated with the plasma time is roughly 1-3 ns from the formation of tracks in the detector until the formation of the pulse rise time.^{74,75,76,77,78,79}

When the charge is finally separated across the collector, the charge separation is not large enough to cause a significant voltage to measure. There needs to be an amplification step

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before acquisition of data, this amplification is often termed the preamplification step. Preamplifiers are placed as near as possible to the detectors, to minimize the contribution of noise to the signal. A good preamplifier will not shape the pulse to any great extent, and its rise time should be as short as possible. Preamplifiers used in these experiments were the chargesensitive (also known as charge-to-voltage) type. The basic concept of a preamplifier is shown in Figure 4.10



Figure 4.10 The elements of a charge-to-voltage preamplifier is shown.

The output voltage (V_{out}) is simply proportional to the amount of charge (Q) across the detector, that migrated to the applied voltage across it (V_{in}), the exact relationship is given in equation 4.11.⁸⁰

$$V_{max} = \frac{Q}{C}$$
(4.11)

 R_f and C_f will control the decay rate or tail of the pulse out from the preamplifier, with a time constant that is equal to R_fC_f .

Once the voltage was generated with a preamplifier it is then necessary to construct a circuit that could hold that energy, collected from the alpha-detectors, long enough for the data acquisition system to measure it. The circuit constructed was a peak-and-hold circuit and utilized the integrated circuit PKD-01, the circuit made is shown in Figure 4.11.



Figure 4.11 Circuit diagram of the shaping amplifier used for the gas-phase experiments.

The final shaping amplifier circuit board held three PKD-01s and was used to collect data from the alpha detectors on the alpha-wheel apparatus; a picture of the circuit is shown in Figure 4.12.



Figure 4.12 A picture of the 3-channel PKD-01 circuit designed, constructed, and used for gasphase experiments.

The shaping amp could hold the maximum voltage collected from the alpha-detectors for several seconds until the signal began to droop. Since the DAQ was sampling every 10-15 ms it was more than enough for our needs. It should be noted that the number of events we were expecting were one event every minute in a low background, thus this type of setup would not be advisable for high-count rate experiments or high background experiments.

4.5 Data Acquisition System Hardware

Data are acquired using a modified National Instruments USB-6009, shown in Figure 4.13. The hardware was modified to accept digital signals from Bayonet Neill-Concelman (BNC) cables and to output digital signals using BNC cables. The USB-6009 stored information in a its buffer and communicated the data being collected to the computer through a Universal Serial Bus (USB) connection.



Figure 4.13 A picture of the modified NI USB-6009.

For any data acquisition system there will be a minimum time required so that when two separate events occur they are measured as two separate and distinct pulses. The minimum time is often called the dead time and for the NI USB-6009 it was sampled approximately every 15 ms. As radioactivity is a random statistical process, there is always a small probability that two nuclei will decay at nearly the same time, making separate observations of both separate decays nearly impossible; this can also happen in high-background experiments or any time a large count rate is expected. When a decay is lost in this fashion it is called a "dead time loss".

There are two types of dead times, paralyzable and nonparalyzable response. In a detector

a fixed time τ follows any event until the detector becomes ready for more events, when this occurs the detector is termed *live*. In a paralyzable detector when the pulses come within τ , they will stack on top of each other and make the observed peak larger than what actually occurred. In a nonparalyzable response any events that come within τ will be ignored until the event has been sampled and the detector resets into a state where it can receive signals again. Both type of dead time responses are shown in Figure 4.14.



Figure 4.14 The measured pulse heights as seen for a fictitious series of events measured in the detector illustrating the concept of dead time.

In the figure there are 4 events at the detector, some within the dead time of the detector. For a paralyzable detector setup this would have meant only two events were observed, and the energy of the second would have been greater than that of any associated event. For a nonparalyzable decay the example would have led to 3 measured events, all corresponding to the energy of an event.

It is important to note that these models are idealized versions of how detectors respond during the dead-time. For the peak shaping circuit that I designed and explained in 4.3.1, the response to a pulse in the dead time would have been nonparalyzable unless the second pulse was larger than the first, and in that case the peak intensity would have risen to that of the highest peak; which is typical for a peak-and-hold circuit.

There are expressions that describe the true rate of events (*n*) for both detector types if you recorded the count rate (*m*) and know the dead time (τ); see equation 4.8 for the nonparalyzable model and equation 4.9 for paralyzable model.

$$n = \frac{m}{1 - m\tau} \tag{4.12}$$

$$m = ne^{-n\tau}$$
 (4.13)

For the experiment presented later, the rate of events was low enough (5 per minute) that the dead time (~15 ms) was not a major concern.

4.6 Data Acquisition System Program (.exe)

The code for the data acquisition system program used for the Gas-Phase experiments (discussed later in this chapter) is shown in Appendix I. The code was written in Visual Basic (VB), because of its superior end user interface. Visual Basic is an event-driven programming language from Microsoft, meaning that with simple clicks and inputs a user has easy control over which part of the code that will be executed. The Visual basic language is considered one of the easier computer languages to learn, due to its origins in Beginner's All-purpose Symbolic Instruction Code (BASIC).

A nice feature of Visual Basic is the ability to make programs that are executable that

work across Windows platforms. So a program that is developed on one computer will work on any other windows computer without the need of installing any additional software; all that is needed is the one executable file. The first version of Visual Basic, v. 1.0, was released in 1991; the version used for this work is Visual Basic .Net which was released in 2008.

· ·	
Help Stepper Controls Run Controls Rate: 25 ms/pin T1/2: 5.0 sec	D.A.Q. Parameters Physical Channel: Dev1/ai0 ✓ Event Threshold: 2.00 ♀ Minimum (Volts): 0.00 ♀ Maximum (Volts): 10.00 ♀
1 0011 3 1100 2 0110 4 1001 Image: Comparison of the second se	Real Time D.A.Q ✓ Enable Real Time D.A.Q. (Slows down performance!) Ch0: Ch2: Ch1: Ch3: Ch5: Ch7:
Quarter Step Completion: 00.0% Completed Rotations: 0 Port Firing: null Total Fired: 0	File Name and Digital Resets C:\Documents and Settings\Mitch\Desktop\data0.txt DI Out 0 1 2 3 4 5 6 7 r
Chnnl: Signal / Time Stmp / Event \$	

Figure 4.15 A screen shot of the data acquisition system used to acquire data.

The program is divided into different sections that have different functions, a different color is associated with the different sections. The sections are Stepper Controls (Green), Run Control (blue), D.A.Q. Parameters (Peach), Real Time D.A.Q. (Pink), Stepper Diagnostics (White), File Name and Digital Resets (cyan), Signal/Time.Stamp/Event# (Yellow).

The Stepper Controls section controls the rate of rotation of the circular sample holder across the alpha-detectors. The stepper motor makes 180 turns before it returns to its starting position. Because the alpha-wheel apparatus has four detectors, it needs to rotate 90 degrees and accomplishes this with 45 little steps. Once it reaches a detector, it stops rotating, collects data, and after a predetermined amount of time it begins to rotate in front of the next detector, and so on. The parameter listed as "Rate" is how long in milliseconds to wait until sending a signal to the motor to make one little step; the default setting is 25 ms. Thus it takes our device 45 x 25 ms, or 1.1 s, to turn and place the sample in front of the next detector. The length of time the sample is to be in front of a detector is determined by the "T1/2" parameter. The parameter is oddly named because the length of time we kept our samples in front of the detector was for the half-life of the element of interest. The buttons labeled "1", "2", "3", "4" were used to manually turn the wheel if we so desired, but the typical use was for the program to use the default setting parameters of "Rate" and "T1/2".

The Stepper Diagnostics section monitors the progress of the sample holder in the alphawheel apparatus. The "Full Rotation Completion" parameter keeps track of where the sample holder is in relation to where it began turning; the value is measured in percent from 0% to 100% and correlates with the sample wheel's rotation of 0 to 360 degrees. The "Quarter Step Completion" parameter keeps track of where the sample holder is when it begins to move the sample from one detector to the next detector; The value is measured in percent from 0 to 100% and correlates with the sample wheel's rotation of 0 - 90 degrees, or 90 - 180 degrees, or 180 -

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270 degrees, or 270 – 360 degrees. The "Completed Rotation" parameter kept track of how many 360 degree turns the sample holder in the alpha-wheel apparatus made. The "Total Fired" parameter kept track of the total number of signals we sent to the stepper motor, each signal corresponded to a stepper motor step. The "port firing" parameter displays which pins of the parallel port is used to send the signal to the stepper-motor driver.

The Run Controls section deals with the actual running, and stopping of the program. Once the "start" button is pressed the stepper motor would begin to turn, using the predefined variables, and the program would begin to acquire the raw voltage signals from the DAQ device, see lines 1589 to 1604 in Appendix I for more information. Pressing "stop" would stop the motor from turning and stop collection of data from the DAQ device, see lines 1539-1545 in Appendix I for more information. The "Reset" button would return all editable parameters back to default.

The D.A.Q. Parameters section deals with the actual DAQ device. The device has eight analog inputs and the parameter labeled "Physical Channel" determines which one of the eight is sampled; the default is channel 0, and is shown as "Dev1/ai0". In order to sample all channels the "Physical Pamater needs to be edited as so, "Dev1/ai0:7". The "Minimum (Volts)" and "Maximum (Volts)" parameter tells the device from what range to expect signals, the device can accept any voltage between -10 V and 10 V. The design of our circuits insured only positive signals, thus the default "Minimum (Volts)" parameter is set to 0.00 V. The "Event Threshold (Volts)" parameter is the signal strength necessary in order for the program to consider an event real and record the data to a file.

The Real Time D.A.Q. Section is meant to allow the user to view the signals that the DAQ device's analog inputs is collecting in real time. It is only useful for debugging the device and was never used when collecting actual data as it was resource intensive and slowed down the computer considerably.

The File Name and Digital Resets section controlled where the data was saved and it could sent a signal to a peak-and-hold circuit to let go of the signal it collected. The location of the data file and the name of the data file could be edited by simply clicking the label displaying the default location (*i.e.* C:\Documents and Settings\Mitch\Desktop\data0.txt"). The design of the circuits prior to the DAQ device sampling involved a peak-and-hold circuit that held the voltage from the alpha-detector long enough for the DAQ device to sample it and send it to the DAQ program. Sampling was done every 10-15 ms on average. When the DAQ program detected an event above the "Event Threshold (Volts)" parameter it would record the event to file and then send a signal to the peak-and-hold to release that voltage. This process was visually seen by a check-mark that flashed on the screen corresponding to which channel had just been told to reset its peak-and-hold circuit. The "DI Out" button is for manually reseting the peak-and-hold and is used by check-marking the appropriate channel and then clicking the button.

The section with the label "Signal/Time.Stamp/Event#" is where the output of events the program believed to be real would appear in real-time. When the program comes across an event that is above the "Event Threshold (Volts)" parameter it will first save the data to file and then display it in this section of the program, see line1304-1310 in Appendix I for more information.

4.7 Data File Structure and Data Analysis Program

The data files stored 6 types of information: whether the heavy-ion beam was on target, the detector/channel an event occurred, the energy of that event, the unique time the event was detected in milliseconds, and a unique event number that was assigned, and at what time the sample holder started to make a 90 degree step, as shown in Figure 4.16.

75

beam-on	440331984		
stepped	440331984		
stepped	440337375		
stepped	440342765		
0: 7.026639	59906771	440345203	2502
stepped	440348187		
beam-on	440353578		
stepped	440353578		
stepped	440358968		
stepped	440364359		
stepped	440369750		
2: 7.724900	11947199	440374812	5415

Figure 4.16 An image of a typical data file.

After the run the files were placed onto FTP to allow other experimenters access to the files. A website was created to read the files and process it using a web browser. An image of the web browser interface is shown below Figure 4.17.

The files were processed using the language of php. By selecting for the parameters of interest above plots of counts versus alpha-energy were generated on the server and displayed back to the end user. The graphics program used was written by me and were generated pixel by pixel; the total cost in server time to run the script is less than 1s. The script also displays relevant information such as: the bin size, detector channel, largest peak, total events in the file, name of the data file analyzed, and associated image information, as shown in Figure 4.18.

Google 👝 🛙	
← → C ☆ http://www.chemistry-blog.com/d ► □	· & ·
Data Analysis Select a File	3
Run FilesChanngp-run2/.0:gp-run2/data0.txt0:gp-run2/data1.txt2:gp-run2/data10.txt0:gp-run2/data11.txt0:gp-run2/data12.txt0:Select Bin SizeBin Size (mV):	
Peak Integration Integrate (min):	

Figure 4.17 A screen shot of the web browser interface for analyzing data files.



Figure 4.18 A screen shot of a typical spectrum generated from the data analysis program. The y-axis is counts and the x-axis is alpha-energy in (keV).

4.8 Experiments with the Alpha-Wheel Apparatus

At the 88-inch cyclotron, Fr-205 was produced to test the alpha-wheel apparatus. Francium-205 was used as a model for rutherfordium-261. Fr-205 has a half-life of 3.85 s and an alpha-energy of 7.01 MeV, while Rf-261 has a half-life of 75 s and an alpha-energy of 8.7 MeV.⁸¹ The nuclear reaction was ¹⁶⁹Tm(⁴⁰Ar, 4n)²⁰⁵Fr. Once francium was made using the BGS it was separated based on magnetic rigidity and stopped/thermalized in helium gas in the recoil transport chamber (RTC). The RTC then contained the francium atoms and an atmosphere of helium, into this chamber aerosol particles of potassium chloride were flushed in at a temperature of ~ 500 °C. The francium atoms would then attach to the aerosol particles and were transported from the BGS to the alpha-wheel apparatus via gas-jet. At the end of the gas-jet transport, the aerosols were deposited onto the thin Mylar film of the rotating sample holder and passed in front of the detectors as described earlier in this chapter.

The parameters of the experiment were as follows. The ⁴⁰Ar beam was turned on for 2 s and then kept off for 16 s. Thus with a step-time of 4 s the aerosol spot would travel in front of all the detectors and back to the collection spot, at which time the beam would be turned on again and the process would be repeated. At the 1st step the aerosol spot would be at detector-1 and the data recording would be collected. At the 2nd step the sample spot would be moved to detector-2 and data would be collected and so on. A typical spectrum collected from the experiment is shown in Figure 4.19



Figure 4.19 This shows the alpha spectrum collected from the ¹⁶⁹Tm(⁴⁰Ar, 4n)²⁰⁵Fr nuclear reaction.

This histogram graphs the number of events recorded at specific alpha-energies. It uses a bin size of 4 mV corresponding 4 keV. As seen above, there is a peak at 6820 keV corresponding to Fr-205's 7.01 MeV alpha. The decrease in energy is likely due to the alpha-spectrum being taken in a flow of gas rather than in a vacuum. A table of all the events corresponding to Francium-205 is shown in Table 4.1.

Total Events	Detector 1	Detector 2	Detector 3
Group 1	129	21	35

Table 4.1 Shows a tabulation of all the events collected for the run.

A post run analysis on detector-2 found that channel to be unreliable and data collected from it was not incorporated in any subsequent analysis. The 129 events collected after turning the beam off and after waiting eight seconds corresponds to ~2 half-lives of Fr-205. By the time it reaches detector-3 approximately 4 half-lives have passed. As the number of events in detector-3 correspond roughly to ¼ of the number of events detected in detector-1, we have strong confidence that all our systems, aside from channel-2, were operating effectively.

4.9 Conclusion

From the ¹⁶⁹Tm(⁴⁰Ar, 4n)²⁰⁵Fr nuclear reaction, we have shown that it is possible to transport radionuclides quickly and efficiently to the constructed alpha-wheel apparatus. We

have also shown that the electronics and circuits constructed are reasonably reliable and work well. These hardware and electronic systems may be on interest to future nuclear scientists as they were mostly constructed using common components found in local electronic stores; the electronics also utilized newer methods of communicating to computers like USB instead of complicated PC cards; finally the electronics were free of the nuclear instrumental module (NIM) standard and could often simply be plugged into a wall. The information learned from the gas-phase experiments will be useful for future investigations into the chemical properties of the heaviest elements in the gas-phase.

Chapter 5: Production of ²⁶¹Rf from ²³⁸U(²⁶Mg, 3n)²⁶¹Rf

5.1 Introduction

The Berkeley Gas-Filled Separator (BGS) was used extensively for this work, and a summary of the device follows. The BGS utilizes three magnets to separate the heavy-ion beam from complete fusion evaporation products; the process has been described previously by Gregorich *et al.*.⁸² A figure of the device is shown in Figure 5.1



Figure 5.1 A schematic of the Berkeley Gas-Filled Separator in the configuration used for the work in this chapter.

The target section of the BGS housed a rotating wheel nine arc-shaped uranium(IV) tetrafluoride targets. The wheel usually rotated at 450 rpm. As a high intensity heavy-ion beam passes through a target it will deposit some of its energy as heat, as the wheel rotates it dissipates

a significant fraction of that heat across the other eight targets; this helps keep the uranium targets from melting. The uranium targets were deposited onto an aluminum backing. Details on the thicknesses of the uranium tetrafluoride targets and aluminum backings can be found in section 5.2.1

The Rutherford detectors are located after the target at an angle of ~27 degrees from the path of the beam (beam axis). The Rutherford detectors are silicon semiconductor detectors that have been thoroughly introduced in chapter 4. They are termed Rutherford detectors because they monitor the Rutherford scattering that occurs as the beam passes through the target. As the positive heavy-ions in the beam transverse the target they will often strike an atomic nucleus within the target and scatter as a simple 3-dimensional kinematics problem. The Rutherford detectors have four grids of wire mesh covering, this is to decrease the rate of scattered beam particles hitting the detectors; without the grids the scattered particles influx would be sufficient to cause excessive radiation damage to the detectors.

The rate of Rutherford scattering (R_{Ruth}) is a direct function of the cross-section of the scattering (σ_{Ruth}), the number of atoms in the target per unit area (N_t), and the intensity of the beam (I). Since the total rate of Rutherford scattering across all angles is not known (because we only have Rutherford detectors at one angle), it is necessary to use the differential Rutherford scattering model.⁸³

$$\frac{d\sigma}{d\omega} = \left[\frac{e^2 Z_1 Z_2}{4\pi\epsilon_0 (2E_{lab})}\right] \frac{1}{\sin^4 \theta} \frac{[\cos \theta + \sqrt{1 - (m_1/m_2)^2 \sin^2 \theta}]^2}{\sqrt{1 - (m_1/m_2)^2 \sin^2 \theta}}$$
(5.1)

The term $d\omega$ is the solid angle differential, Z_1 and Z_2 are the atomic number of the projectile and target respectively, E_{lab} is the energy in the laboratory frame of the beam, m_1 and m_2 are the

masses of the projectile and target respectively, θ is the angle of the Rutherford detectors from the beam axis in the laboratory frame. Equation 5.1 only holds true when the mass of the projectile is less than the mass of the target.

As matter mainly consists of empty space the beam will mainly pass through the thin target material without any interaction. Compared to the rate of no reaction, the scattering rate is comparatively several magnitudes smaller, smaller yet is the magnitude of the rate of compound nucleus formation. When proper compound nucleus formation does occur, the evaporation of the proper number of neutrons without fission, it creates the isotope of interest (in the case of this chapter rutherfordium). The next task of the BGS is to separate the beam from the rutherfordium ions, this is accomplished through the use of the three BGS magnets. The magnets include a quadrupole magnet (Q1), followed by a gradient field dipole magnet (M1), and followed by a flat field dipole magnet (M2). The quadrupole magnet is oriented in such a way that it focuses the rutherfordium ions get physically separated from the beam by the next magnets (M1 and M2). The magnets applies a different net Lorentz force on the beam and rutherfordium ions, the Lorentz force is given in equation 5.2.

$$F = qvB$$
 (5.2)

The term q is the charge of the particle, v is the velocity of the particle, and B is the magnitude of the magnetic field. The Lorentz force is equally balanced by the centripetal force, given in equation 5.3.

$$F = \frac{mv^2}{\rho} \tag{5.3}$$

The term *m* is the particle's mass, *v* is the velocity of the particle, and ρ is the radius of curvature of the motion of the particle. As ρ is fixed by the physical design of the BGS, by careful selection of *B* it is possible to have high separation factors. The overall configuration of the BGS allows for a physical separation factor on the order of ~10¹⁴, due in part to the large bending angle of the BGS 70°.

The charge state of the beam particles are known exactly, due to the cyclotron selecting for only one type of charge state. However, the charge state of rutherfordium as it leaves the target material is an other matter. The momentum of rutherfordium is much lower than the beam particles, so that interactions with the gas molecules within the BGS will cause rutherfordium to pick up several electrons. In order to account for this we use the concept of average charge state (q_{avg}) . The average charge state is simply the average of the discrete charges on rutherfordium atoms as it transverses the BGS. An equation for the average charge state used in these experiments is given in equation 5.4.⁸⁴

$$q_{avg} = px + r + s \sin\left(\frac{2\pi}{32}[Z - (px + r) - t]\right)$$
(5.4)

The equation is a semi-empirical fit to the measured q_{avg} . The term *p* is equal to 0.641, *x* is equal to $vZ^{1/3}$ where *v* is the velocity expressed in Bohr velocity and *Z* is the atomic number of the particle, *r* is -0.235, *s* is 0.517, *t* is 74.6.

The research group has developed equations to determine the amount of current needed to power each magnet in order to have good separation based on the magnetic rigidity of the element of interest once the average charge state has been calculated.

$$I(Q1) = 765mv/q_{avg}$$
 (5.5)

$$I(M1) = \frac{mv/q_{avg}}{0.002467 + 0.002016R}$$
(5.6)

$$I(M2) = \frac{mv/q_{avg}}{0.002467/R + 0.002016}$$
(5.7)

The term mv is the momentum of the charged particle, and R is an experimentally determined constant and has been found to be 1.69. With all this information it is possible to separate out rutherfordium atoms and pass them to the detectors for detection.

The detectors used for the focal plane, at the end of the BGS, were of the silicon semiconductor variety. An picture of the detector array is shown in Figure 5.2



Figure 5.2 This shows a picture of the focal plane detector. The silicon semiconductor detectors can be seen to be arrayed in an open rectangular box.

The detectors are arrayed in an open rectangular box configuration of detector "cards". The detector cards are 60 mm x 60 mm and each is divided equally into 16 strips. Each strip is 3.265 mm long and can be used to determine the position of a decay within the detector array. The

detectors are externally reverse biased to 40 V.

The data acquisition system differs from that explained in chapter 4. Similarly, as decays occur in the detector array the charge is converted to voltage by the use of preamplifiers. However, after the preamplifiers the signal is sent to a CAEN N568B amplifier. This module creates a fast pulse that is sent to a MSU 1806 constant fraction discriminator (CFD). In order for data collection to begin the CFD must receive a voltage that is above a minimal threshold; if such a signal exists it is sent to a trigger module.⁸⁵ The dead time for acquisition is 11 µs. A slow pulse is sent to the CAEN V785 analog digital converters (ADCs) for digitalization of the analog voltage. It is possible to view the data as it comes in real-time with the Multi Branch System (MBS) program.^{86,87} The MBS is programmed to search for alpha-alpha correlations or alpha-spontaneous fission correlations under certain parameters described in the next section. When the MBS detects a possible correlation, it can shut off the beam in order to remove background noise caused by beam particles that were not effectiveley removed by the magnets. The MBS is installed on a RIO2 computer running the Lynx-OS operating system.

5.2 Experimental Setup

Beams of magnesium (²⁶Mg⁶⁺) were produced from enriched metallic Mg in the Advanced Electron Cyclotron Resonance (AECR) ion source and then accelerated by the 88-Inch Cyclotron at Lawrence Berkeley National Laboratory(LBNL) to energies of 4.9–6.0 MeV/nucleon. The beam passed through a 45 μ g/cm² thick carbon (C) window at the entrance of the Berkeley Gas-filled Separator (BGS)^{88,89} that serves to separate the vacuum of the beam line from the 66-Pa helium(He) gas inside the BGS. Approximately one centimeter downstream of the entrance window was a rotating (~10 Hz)target wheel consisting of nine arc-shaped uranium(IV) tetrafluoride (UF₄, ~470µg/cm2) targets. These targets were prepared by evaporation of UF₄ onto 580-µg/cm² aluminum(Al) foils. The energy thickness of the UF₄ layer on each target segment was approximately 2.0 MeV.

Typical beam intensities ranged from 0.5 to 1.0 particle- μ A. Energy losses in carbon, aluminum, and uranium tetrafluoride were calculated with SRIM2006.02.⁹⁰ The product of target thickness and beam intensity was monitored on-line by the detection of Rutherford-scattered particles in two PIN diode detectors located at ±27° from the beam axis. Analysis of the pulse heights of the Rutherford-scattered projectiles from the various ²⁶Mg beam energies gives relative energies to within 0.1%. The resulting center-of-target beam energy was 121.8 MeV in the laboratory frame. Systematic uncertainty in the energies from the 88-Inch Cyclotron is estimated to be ~1%. Compound nucleus excitation energies were calculated using the relative beam energies with the experimental mass defects for ²⁶Mg and ²³⁸U and the Thomas-Fermi mass defects for the compound nucleus.^{91,92} The resulting ranges of compound nucleus excitation energy within the targets was 35.3 ± 0.9.

Rutherfordium compound nucleus evaporation residues(EVRs) were formed with the momentum of the projectile and recoil from the target. These EVRs were separated from the beam and other unwanted reaction products in the BGS based upon their differing magnetic rigidities in He gas. The magnetic rigidity of the rutherfordium EVRs was estimated as previously described.⁹³ The efficiency for collecting rutherfordium EVRs at the BGS focal plane was modeled using a Monte Carlo simulation of the EVR trajectories in the BGS, as described earlier,⁹⁴ and resulted in an efficiency of 15%. Details of the Si-strip detector array and data acquisition system have been reported elsewhere.⁹⁵ The rutherfordium EVRs have a short range and low implantation energy in the focal plane detector due to their low kinetic energy. Thus, a multiwire proportional counter could not be used and no information was available to help differentiate between implantation events and decay events of similar energy within the focal

plane detector.

The search for EVR- α and EVR- α - α correlations was expected to be hindered by random correlations of events unrelated to the decay of the desired nuclides. This problem was circumvented by using a pulsed beam that had a 50% duty factor with a period of 600 ms. Searching for α -particles between beam pulses led to a significant background reduction and allowed the identification of the α -emitting nuclides. To further reduce random correlations during the pulsed irradiations, α -decays were defined as events anticoincident with the upstream detectors (*i.e.*, the full energy of the α -decay was required to be in the focal plane detector and not split between the focal plane and upstream detectors). A fast shutoff mode was employed to search for ²⁶¹Rf. During this mode, the beam was shut off for 100 s after detection of an EVR [3.5 < E(MeV) < 10.0, during the beam pulse] followed by the observation of an α -particle [8.0 < E(MeV) < 9.0, in-between beam pulses] in the same strip and within 300 s and ±3.5 mm of the EVR. This allowed for the detection of the 25 s half-life of ²⁵⁷No daughter in nearly background free conditions.⁹⁶

5.3 Results

²⁶¹Rf was produced in the ²⁶Mg(²³⁸U, 3n)²⁶¹Rf reaction at the lowest excitation energy of 35.3 MeV. The direct production of ²⁶¹Rf from a 3n hot-fusion exit-channel has not been observed previously. Two isomers are known for ²⁶¹Rf. The first isomer, designated ^{261a}Rf, decays by either SF or α-particle emission (Eα = 8.51 MeV, Iα =0.09, $T_{1/2}$ = 2.8 s).⁹⁷ The second isomer, designated ^{261b}Rf, has only been observed to decay by α-particle emission (Eα = 8.3 MeV, $T_{1/2}$ = 75 ± 7 s), with an upper limit of 11% for decay by SF.⁹⁸,⁹⁹

We observed one correlated EVR- α - α decay chain with the following decay properties: ²⁶¹Rf (E α = 8.34 ± 0.05 MeV, τ = 103.2 s), 257No (E α = 8.30 ± 0.05 MeV, τ = 12.2 s). This event was assigned to ^{261b}Rf and corresponds to a cross section of 28 pb. A second event consisted of an EVR-SF decay chain with a SF energy of 173.3 MeV and a life time of 9.4 s. This event could be assigned to either isomer of ²⁶¹Rf. However, as discussed in the following section, there is only a 6% probability for observing a random EVR-SF correlation within five half-lives of ^{261a}Rf. If confirmed, this would represent the first observation of this isomer produced as an EVR. The addition of this second event would only increase the 3n cross section by 14%, to 32 pb.

5.4 Conclusion

Historical precedence indicates that the 3n exit channel cross sections rapidly decrease with increasing $Z_{projectile}$.^{100-101,102} Recently, Dvorak *et al*.⁹⁰ have made the surprising observation of a 3n exit channel in the ²⁴⁸Cm(²⁶Mg, 3n)²⁷¹Hs reaction, with a cross section that is comparable in magnitude to the 4n cross section. In this work, a dedicated irradiation searching for the 3n exit channel of the ²⁶Mg + ²³⁸U reaction was performed. ²⁶¹Rf was observed to have a cross section of 28 pb at a beam energy of 121.8 MeV. These discoveries open the possibility of accessing longlived neutron-rich nuclides of the transactinides utilizing hot fusion reactions with neutron-rich targets.

1 Appendinx I – Visual Basic Code for Data Acquisition Sustem

- 2 Imports NationalInstruments.DAQmx
- 3 Imports System.Math
- 4 Public Class MainForm
- 5 Inherits System.Windows.Forms.Form
- 6 Private myTask As Task 'Main Task which is Assigned when the Start Button is Clicked
- 7 Private myTask2 As Task 'Main Task which is Assigned when the Start Button is Clicked
- 8 Private runningTask As Task 'Mitch added for the 100 sample catch
- 9 Private analogInReader As AnalogMultiChannelReader 'Mitch added for the 100 sample catch
- 10 Private analogCallback As AsyncCallback 'Mitch added for the 100 sample catch
- 11 Private data100 As Double(,) 'Mitch added for the 100 sample catch
- 12 Dim reader2 As AnalogMultiChannelReader 'Mitch added for the 100 sample catch
- 13 Dim reader As AnalogMultiChannelReader
- 14 Private totalSamples As Int32 'Global Container for the number samples to be acquired
- 15 Private acquiredSamplesCount As Int32 = 0 'Iteration variable which hold the current sample being acquired
- 16 Private dataColumn As DataColumn()
- 17 Friend WithEvents runcontrols As System.Windows.Forms.GroupBox
- 18 Friend WithEvents Label11 As System.Windows.Forms.Label
- 19 Friend WithEvents halflife As System.Windows.Forms.NumericUpDown
- 20 Friend WithEvents Label10 As System.Windows.Forms.Label
- 21 Friend WithEvents reset As System.Windows.Forms.Button
- 22 Friend WithEvents boxtimer As System.Windows.Forms.NumericUpDown
- 23 Friend WithEvents Label2 As System.Windows.Forms.Label
- 24 Friend WithEvents stopbutton2 As System.Windows.Forms.Button
- 25 Friend WithEvents Label1 As System.Windows.Forms.Label
- 26 Friend WithEvents GroupBox4 As System.Windows.Forms.GroupBox
- 27 Friend WithEvents Label27 As System.Windows.Forms.Label
- 28 Friend WithEvents Label28 As System.Windows.Forms.Label
- 29 Friend WithEvents Label25 As System.Windows.Forms.Label
- 30 Friend WithEvents Label26 As System.Windows.Forms.Label
- 31 Friend WithEvents Label23 As System.Windows.Forms.Label
- 32 Friend WithEvents Label24 As System.Windows.Forms.Label
- 33 Friend WithEvents Label22 As System.Windows.Forms.Label
- 34 Friend WithEvents Label21 As System.Windows.Forms.Label
- 35 Friend WithEvents daq7 As System.Windows.Forms.TextBox
- Friend WithEvents daq6 As System.Windows.Forms.TextBox
 Friend WithEvents daq5 As System.Windows.Forms.TextBox
- Friend WithEvents daq5 As System.Windows.Forms.TextBox
 Friend WithEvents daq4 As System.Windows.Forms.TextBox
- Friend WithEvents daq4 As System.Windows.Forms.TextBox
 Friend WithEvents daq3 As System.Windows.Forms.TextBox
- 40 Friend WithEvents daq2 As System. Windows.Forms.TextBox
- 41 Friend WithEvents daq1 As System. Windows. Forms. TextBox 41 Friend WithEvents daq1 As System. Windows. Forms. TextBox
- 42 Friend WithEvents daq0 As System. Windows. Forms. TextBox
- 43 Friend WithEvents dagenable As System.Windows.Forms.CheckBox
- 44 Friend WithEvents TextBox2 As System.Windows.Forms.TextBox
- 45 Friend WithEvents TextBox1 As System.Windows.Forms.TextBox
- 46 Friend WithEvents GroupBox3 As System.Windows.Forms.GroupBox
- 47 Friend WithEvents Label17 As System.Windows.Forms.Label
- 48 Friend WithEvents Labelbarstep As System.Windows.Forms.Label
- 49 Friend WithEvents barstep As System.Windows.Forms.ProgressBar
- 50 Friend WithEvents Label16 As System.Windows.Forms.Label
- 51 Friend WithEvents Label15 As System.Windows.Forms.Label
- 52 Friend WithEvents Labelbarfull As System.Windows.Forms.Label

53 Friend WithEvents boxcomfull As System.Windows.Forms.TextBox 54 Friend WithEvents Label14 As System.Windows.Forms.Label 55 Friend WithEvents Label13 As System.Windows.Forms.Label 56 Friend WithEvents barfull As System.Windows.Forms.ProgressBar 57 Friend WithEvents Button6 As System.Windows.Forms.Button 58 Friend WithEvents boxtfire As System.Windows.Forms.TextBox 59 Friend WithEvents Label9 As System.Windows.Forms.Label 60 Friend WithEvents boxport As System.Windows.Forms.TextBox Friend WithEvents Label8 As System.Windows.Forms.Label 61 62 Friend WithEvents Label7 As System.Windows.Forms.Label Friend WithEvents Label6 As System.Windows.Forms.Label 63 Friend WithEvents Label5 As System.Windows.Forms.Label 64 Friend WithEvents Label4 As System.Windows.Forms.Label 65 Friend WithEvents Button2 As System.Windows.Forms.Button 66 67 Friend WithEvents Button5 As System.Windows.Forms.Button 68 Friend WithEvents Button3 As System.Windows.Forms.Button Friend WithEvents Button4 As System.Windows.Forms.Button 69 70 Friend WithEvents Label29 As System.Windows.Forms.Label Friend WithEvents threshold As System.Windows.Forms.NumericUpDown 71 Friend WithEvents Timer1 As System.Windows.Forms.Timer 72 Friend WithEvents timerstep As System.Windows.Forms.Timer 73 Friend WithEvents Button1 As System.Windows.Forms.Button 74 Friend WithEvents MasterControls As System.Windows.Forms.GroupBox 75 Friend WithEvents MenuStrip1 As System.Windows.Forms.MenuStrip 76 77 Friend WithEvents HelpToolStripMenuItem As System.Windows.Forms.ToolStripMenuItem 78 Friend WithEvents samples100 As System.Windows.Forms.Timer 79 Friend WithEvents bit0CheckBox As System.Windows.Forms.CheckBox Friend WithEvents bit1CheckBox As System.Windows.Forms.CheckBox 80 81 Friend WithEvents bit2CheckBox As System.Windows.Forms.CheckBox 82 Friend WithEvents bit3CheckBox As System.Windows.Forms.CheckBox Friend WithEvents bit4CheckBox As System.Windows.Forms.CheckBox 83 Friend WithEvents bit5CheckBox As System.Windows.Forms.CheckBox 84 Friend WithEvents bit6CheckBox As System.Windows.Forms.CheckBox 85 86 Friend WithEvents bit7CheckBox As System.Windows.Forms.CheckBox 87 Friend WithEvents writeButton As System.Windows.Forms.Button Friend WithEvents rstckbx As System.Windows.Forms.CheckBox 88 Friend WithEvents GroupBox1 As System.Windows.Forms.GroupBox 89 Friend WithEvents tbfilename As System.Windows.Forms.TextBox 90 91 Friend WithEvents beam As System.Windows.Forms.TextBox

- 92 'Channels of Data
- 93 Private dataTable As DataTable = New DataTable 'Table to Display Data
- 94 #Region " Windows Form Designer generated code "
- 95 Public Sub New()
- 96 MyBase.New()
- 97 Application.EnableVisualStyles()
- 98 'This call is required by the Windows Form Designer.
- 99 InitializeComponent()
- 100 'Add any initialization after the InitializeComponent() call
- 101 physicalChannelComboBox.Items.AddRange(DaqSystem.Local.GetPhysicalChannels(PhysicalChannelTypes.
- 102 AI, PhysicalChannelAccess.External))
- 103 If (physicalChannelComboBox.Items.Count > 0) Then

104 105	physicalChannelComboBox.SelectedIndex = 0 End If
106	End Sub
107	'Form overrides dispose to clean up the component list.
108	Protected Overloads Overrides Sub Dispose(ByVal disposing As Boolean)
109	If disposing Then
110	If Not (components Is Nothing) Then
111	components.Dispose()
112	End If
113	End If
114 115	MyBase.Dispose(disposing) End Sub
110	
116	Required by the Windows Form Designer
117	Private components As System.ComponentModel.IContainer
118	'NOTE: The following procedure is required by the Windows Form Designer
119	It can be modified using the Windows Form Designer.
120	Do not modify it using the code editor.
121	Friend WithEvents channelParametersGroupBox As System. Windows. Forms. GroupBox
122	Friend WithEvents maximumLabel As System. Windows.Forms.Label
123	Friend WithEvents minimumLabel As System. Windows.Forms.Label
124	Friend WithEvents loopTimer As System Windows Forms Timer
125	Friend WithEvents noop Timer As System, windows.Forms NumericUpDown
120	Friend WithEvents maximum ValueNumeric As System. Windows Forms NumericUpDown
127	Friend WithEvents nhaving Channel Combo Box As System. Windows Forms Combo Box
129	<pre><system debuggerstepthrough()="" diagnostics.=""> Private Sub InitializeComponent()</system></pre>
130	Me.components = New System ComponentModel Container
131	Dim resources As System.ComponentModel.ComponentResourceManager = New
132	System.ComponentModel.ComponentResourceManager(GetType(MainForm))
133	Me.channelParametersGroupBox = New System.Windows.Forms.GroupBox
134	Me.Label29 = New System.Windows.Forms.Label
135	Me.threshold = New System.Windows.Forms.NumericUpDown
136	Me.physicalChannelComboBox = New System.Windows.Forms.ComboBox
137	Me.minimumValueNumeric = New System.Windows.Forms.NumericUpDown
138	Me.maximumValueNumeric = New System.Windows.Forms.NumericUpDown
139	Me.maximumLabel = New System.Windows.Forms.Label
140	Me.minimumLabel = New System.Windows.Forms.Label
141	Me.physicalChannelLabel = New System.Windows.Forms.Label
142	Me.loopTimer = New System.Windows.Forms.Timer(Me.components)
143	Me.runcontrols = New System. Windows.Forms.GroupBox
144	Me.Label11 = New System. Windows.Forms.Label
145	Me.Label / = New System. Windows.Forms.Label Me.halflife - New System Windows Forms.NumerioLipDown
140	Me Button 5 – New System Windows Forms Button
147	Me Label6 – New System Windows Forms Label
140	Me Labell $0 = \text{New System. Windows: Forms: Label}$
150	Me Label5 = New System Windows Forms Label
151	Me.Button4 = New System.Windows.Forms.Button
152	Me.boxtimer = New System, Windows, Forms, NumericUpDown
153	Me.Label4 = New System.Windows.Forms.Label
154	Me.Button3 = New System.Windows.Forms.Button
155	Me.Label2 = New System.Windows.Forms.Label
156 Me.Button2 = New System.Windows.Forms.Button 157 Me.Label1 = New System.Windows.Forms.Label Me.reset = New System.Windows.Forms.Button 158 159 Me.stopbutton2 = New System.Windows.Forms.Button 160 Me.GroupBox4 = New System.Windows.Forms.GroupBox 161 Me.Label27 = New System.Windows.Forms.Label Me.Label28 = New System.Windows.Forms.Label 162 163 Me.Label25 = New System.Windows.Forms.Label 164 Me.Label26 = New System.Windows.Forms.Label 165 Me.Label23 = New System.Windows.Forms.Label Me.Label24 = New System.Windows.Forms.Label 166 167 Me.Label22 = New System.Windows.Forms.Label 168 Me.Label21 = New System.Windows.Forms.Label 169 Me.daq7 = New System.Windows.Forms.TextBox 170 Me.daq6 = New System.Windows.Forms.TextBox 171 Me.daq5 = New System.Windows.Forms.TextBox 172 Me.daq4 = New System.Windows.Forms.TextBox 173 Me.daq3 = New System.Windows.Forms.TextBox 174 Me.daq2 = New System.Windows.Forms.TextBox 175 Me.dag1 = New System.Windows.Forms.TextBox 176 Me.daq0 = New System.Windows.Forms.TextBox 177 Me.daqenable = New System.Windows.Forms.CheckBox Me.TextBox2 = New System.Windows.Forms.TextBox 178 179 Me.TextBox1 = New System.Windows.Forms.TextBox 180 Me.GroupBox3 = New System.Windows.Forms.GroupBox 181 Me.Label17 = New System.Windows.Forms.Label 182 Me.Labelbarstep = New System.Windows.Forms.Label 183 Me.barstep = New System.Windows.Forms.ProgressBar 184 Me.Label16 = New System.Windows.Forms.Label 185 Me.Label15 = New System.Windows.Forms.Label Me.Labelbarfull = New System.Windows.Forms.Label 186 Me.boxcomfull = New System.Windows.Forms.TextBox 187 188 Me.Label14 = New System.Windows.Forms.Label 189 Me.Label13 = New System.Windows.Forms.Label Me.barfull = New System.Windows.Forms.ProgressBar 190 191 Me.Button6 = New System.Windows.Forms.Button 192 Me.boxtfire = New System.Windows.Forms.TextBox 193 Me.Label9 = New System.Windows.Forms.Label 194 Me.boxport = New System.Windows.Forms.TextBox 195 Me.Label8 = New System.Windows.Forms.Label 196 Me.Timer1 = New System.Windows.Forms.Timer(Me.components) 197 Me.timerstep = New System.Windows.Forms.Timer(Me.components) Me.Button1 = New System.Windows.Forms.Button 198 199 Me.MasterControls = New System.Windows.Forms.GroupBox 200 Me.MenuStrip1 = New System.Windows.Forms.MenuStrip 201 Me.HelpToolStripMenuItem = New System.Windows.Forms.ToolStripMenuItem 202 Me.samples100 = New System.Windows.Forms.Timer(Me.components) 203 Me.bit0CheckBox = New System.Windows.Forms.CheckBox 204 Me.bit1CheckBox = New System.Windows.Forms.CheckBox 205 Me.bit2CheckBox = New System.Windows.Forms.CheckBox 206 Me.bit3CheckBox = New System.Windows.Forms.CheckBox 207 Me.bit4CheckBox = New System.Windows.Forms.CheckBox 208 Me.bit5CheckBox = New System.Windows.Forms.CheckBox 209 Me.bit6CheckBox = New System.Windows.Forms.CheckBox 210 Me.bit7CheckBox = New System.Windows.Forms.CheckBox 211 Me.writeButton = New System.Windows.Forms.Button

212	Me.rstckbx = New System.Windows.Forms.CheckBox
213	Me.GroupBox1 = New System.Windows.Forms.GroupBox
214	Me.tbfilename = New System.Windows.Forms.TextBox
215	Me.beam = New System.Windows.Forms.TextBox
216	Me.channelParametersGroupBox.SuspendLayout()
217	CType(Me.threshold, System, ComponentModel, ISupportInitialize), BeginInit()
218	CType(Me minimumValueNumeric, System ComponentModel ISupportInitialize) BeginInit()
210	CType(Me maximum ValueNumeric, System ComponentModel ISupportInitialize) BeginInit()
21)	Me runcontrols Suspend avout()
220	CTure(Ma halflife System ComponentMedal ISupportInitialize) PaginInit()
221	CType(Me.hanne, System.Component/Model ISupportInitialize).DeginInit()
222	Crype(inte.boxtimer, System.Componentwidder.iSupportinitianze).Beginnin()
223	Me.GroupBox4.SuspendLayout()
224	Me.GroupBox3.SuspendLayout()
225	Me.MasterControls.SuspendLayout()
226	Me.MenuStrip1.SuspendLayout()
227	Me.GroupBox1.SuspendLayout()
228	Me.SuspendLayout()
229	1
230	'channelParametersGroupBox
231	
232	Me.channelParametersGroupBox.BackColor = System.Drawing.Color.Transparent
233	Me.channelParametersGroupBox.Controls.Add(Me.Label29)
234	Me.channelParametersGroupBox.Controls.Add(Me.threshold)
235	Me.channelParametersGroupBox.Controls.Add(Me.physicalChannelComboBox)
236	Me.channelParametersGroupBox.Controls.Add(Me.minimumValueNumeric)
237	Me channelParametersGroupBox Controls Add(Me maximumValueNumeric)
238	Me channelParametersGroupBox.Controls Add(Me maximum varder varierie)
230	Me channelParametersGroupBox.Controls Add(Me minimumI abel)
239	Me channelParametersGroupBox.Controls Add(Me nhysicalChannelLabel)
240	Me channel Parameters Group Dox. Controls. Add (Mc.physical Channel Laber) Me channel Deremeters Group Dox. Controls. Add (Mc.physical Channel Laber)
241	Integer), CTure(CTure(102, Bute), Integer), CTure(CTure(102, Bute), Integer))
242	Musley (Crype(Crype(192, Byte), Integer), Crype(Crype(192, Byte), Integer))
243	Me.channelParametersGroupBox.Location = New System.Drawing.Point(321, 28)
244	Me.channelParametersGroupBox.Name = "channelParametersGroupBox"
245	Me.channelParametersGroupBox.Size = New System.Drawing.Size(398, 82)
246	Me.channelParametersGroupBox.TabIndex = 2
247	Me.channelParametersGroupBox.TabStop = False
248	Me.channelParametersGroupBox.Text = "D.A.Q. Parameters"
249	
250	'Label29
251	1
252	Me.Label29.AutoSize = True
253	Me.Label29.Location = New System.Drawing.Point(193, 17)
254	Me.Label29.Name = "Label29"
255	Me.Label29.Size = New System.Drawing.Size(88, 26)
256	Me.Label29.TabIndex = 18
257	Me.Label29.Text = "Event Threshold:" & Global.Microsoft.VisualBasic.ChrW(13) &
258	Global.Microsoft.VisualBasic.ChrW(10) & "(Volts)"
259	· · · · · · · · · · · · · · · · · · ·
260	'threshold
261	1
262	Me threshold BackColor = System Drawing Color From $\Delta rgh(CType(CType(64, Byte), Integer))$
262	CType(CType(64 Ryte) Integer) (CType(64 Ryte) Integer))
205	$\frac{C_{1}}{M_{e}} = \frac{C_{1}}{M_{e}} \frac{C_{1}}{M$
204 265	$\frac{1}{100} = \frac{1}{100} = \frac{1}$
203	$CT_{rmo}(CT_{rmo}(102, \text{Byte}), \text{Integer}), CT_{rmo}(CT_{rmo}(102, \text{Byte}), \text{Integer}),$
200	(1) (1)
/ m /	$\mathbf{h}_{\mathbf{n}} = \mathbf{h}_{\mathbf{n}} $

267 Me.threshold.Increment = New Decimal(New Integer() {1, 0, 0, 65536})

268	Me.threshold.Location = New System.Drawing.Point(291, 15)
269	Me.threshold.Maximum = New Decimal(New Integer() $\{10, 0, 0, 0\}$)
270	Me.threshold.Name = "threshold"
271	Me.threshold.Size = New System.Drawing.Size(96, 20)
272	Me.threshold.TabIndex = 17
273	Me.threshold.Value = New Decimal(New Integer() $\{200, 0, 0, 131072\}$)
274	
275	'physicalChannelComboBox
276	F
277	Me.physicalChannelComboBox.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte),
278	Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
279	Me.physicalChannelComboBox.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte)).
280	Integer) CType(CType(192, Byte) Integer) CType(CType(192, Byte) Integer))
281	Me physicalChannelComboBox Location = New System Drawing Point(96, 15)
282	Me.physicalChannelComboBox.Name = "physicalChannelComboBox"
283	Me physical Channel ComboBox Size = New System Drawing Size(96, 21)
284	Me.physicalChannelComboBox.TabIndex – 1
285	Me.physicalChannelComboBox Text = "Dev1/ai0"
286	
280	'minimumValueNumeric
288	
280	Ma minimumValueNumeric BackColor - System Drawing Color From Argb(CType(CType(64, Byte), Integer)
209	(Type(CType(64, Byte), Integer), (Type(CType(64, Byte), Integer))
290	$M_{e} \min mum Value Numeric Decimal Diaces = 2$
201	Me minimum ValueNumeric EoreColor – System Drawing Color From $\Lambda rab(CType(CType(255, Byte), Integer))$
292	(Type(CType(
293	Ma minimum ValueNumerica Location - New System Drawing Doint(06, 26)
294	Me minimum ValueNumeric Movimum – New Decime1(New Integer() (10, 0, 0, 0))
295	Me minimum ValueNumeric Minimum – New Decimal(New Integer() {10, 0, 0, 0})
290	Me.minimum valueNumeric.Minimum = New Decimal(New Integer() {10, 0, 0, -214/483048})
297	Me minimum ValueNumeric Size = New System Drawing Size(06, 20)
298	Me.minimum value Numeric. Size = New System. Drawing. Size(90, 20)
299	$\frac{1}{1}$
201	lan animum Mala a Numania
202	maximum valuenumeric
302	$\mathbf{M}_{\mathbf{r}} = \mathbf{M}_{\mathbf{r}} = \mathbf{M}_{\mathbf{r}} + \mathbf{M}_{\mathbf{r}} = \mathbf{M}_{\mathbf{r}} + \mathbf{M}_{\mathbf{r}} = \mathbf{M}_{\mathbf{r}} + $
303	Me.maximum valueNumeric.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer),
304	C Type(C Type(64, Byte), Integer), C Type(C Type(64, Byte), Integer))
305	Me.maximum value Numeric. Decimal Places = 2
306	Me.maximum ValueNumeric.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte),
307	Integer), CType(CType(T92, Byte), Integer), CType(CType(T92, Byte), Integer))
308	Me.maximum valueNumeric.Location = New System.Drawing.Point(96, 54)
309	Me.maximum ValueNumeric.Maximum = New Decimal(New Integer() $\{10, 0, 0, 0, 0\}$)
310	Me.maximum ValueNumeric.Minimum = New Decimal(New Integer() $\{10, 0, 0, -214/483648\}$)
311	Me.maximum ValueNumeric.Name = "maximum ValueNumeric"
312	Me.maximum ValueNumeric.Size = New System.Drawing.Size(96, 20)
313	Me.maximum Value Numeric. Tablindex = 5
314	Me.maximumValueNumeric. Value = New Decimal(New Integer() $\{100, 0, 0, 65536\}$)
315	
316	maximumLabel
317	
318	Me.maximumLabel.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
319	CType(CType(192, Byte), Integer), CType(CType(192, Byte), Integer))
320	Me.maximumLabel.Location = New System.Drawing.Point(6, 56)
321	Me.maximumLabel.Name = "maximumLabel"
322	Me.maximumLabel.Size = New System.Drawing.Size(96, 16)

323 Me.maximumLabel.TabIndex = 4

```
324
           Me.maximumLabel.Text = "Maximum (Volts):"
325
326
           'minimumLabel
327
328
           Me.minimumLabel.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
329
      CType(CType(192, Byte), Integer), CType(CType(192, Byte), Integer))
330
           Me.minimumLabel.Location = New System.Drawing.Point(8, 38)
331
           Me.minimumLabel.Name = "minimumLabel"
332
           Me.minimumLabel.Size = New System.Drawing.Size(96, 16)
333
           Me.minimumLabel.TabIndex = 2
           Me.minimumLabel.Text = "Minimum (Volts):"
334
335
336
           'physicalChannelLabel
337
338
           Me.physicalChannelLabel.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
339
      CType(CType(192, Byte), Integer), CType(CType(192, Byte), Integer))
340
           Me.physicalChannelLabel.Location = New System.Drawing.Point(0, 19)
341
           Me.physicalChannelLabel.Name = "physicalChannelLabel"
342
           Me.physicalChannelLabel.Size = New System.Drawing.Size(96, 16)
343
           Me.physicalChannelLabel.TabIndex = 0
344
           Me.physicalChannelLabel.Text = "Physical Channel:"
345
346
           'loopTimer
347
348
           Me.loopTimer.Interval = 1
349
350
           'runcontrols
351
352
           Me.runcontrols.BackColor = System.Drawing.Color.Transparent
353
           Me.runcontrols.Controls.Add(Me.Label11)
354
           Me.runcontrols.Controls.Add(Me.Label7)
355
           Me.runcontrols.Controls.Add(Me.halflife)
356
           Me.runcontrols.Controls.Add(Me.Button5)
357
           Me.runcontrols.Controls.Add(Me.Label6)
358
           Me.runcontrols.Controls.Add(Me.Label10)
359
           Me.runcontrols.Controls.Add(Me.Label5)
360
           Me.runcontrols.Controls.Add(Me.Button4)
361
           Me.runcontrols.Controls.Add(Me.boxtimer)
362
           Me.runcontrols.Controls.Add(Me.Label4)
363
           Me.runcontrols.Controls.Add(Me.Button3)
364
           Me.runcontrols.Controls.Add(Me.Label2)
365
           Me.runcontrols.Controls.Add(Me.Button2)
           Me.runcontrols.Controls.Add(Me.Label1)
366
367
           Me.runcontrols.Font = New System.Drawing.Font("Comic Sans MS", 8.25!,
368
      System.Drawing.FontStyle.Regular, System.Drawing.GraphicsUnit.Point, CType(0, Byte))
           Me.runcontrols.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer),
369
370
      CType(CType(255, Byte), Integer), CType(CType(192, Byte), Integer))
371
           Me.runcontrols.Location = New System.Drawing.Point(8, 28)
372
           Me.runcontrols.Name = "runcontrols"
373
           Me.runcontrols.Size = New System.Drawing.Size(161, 131)
374
           Me.runcontrols.TabIndex = 16
375
           Me.runcontrols.TabStop = False
376
           Me.runcontrols.Text = "Stepper Controls"
377
378
           'Label11
379
```

380 Me.Label11.AutoSize = True 381 Me.Label11.Location = New System.Drawing.Point(120, 40) 382 Me.Label11.Name = "Label11" 383 Me.Label11.Size = New System.Drawing.Size(24, 15) 384 Me.Label11.TabIndex = 17 385 Me.Label11.Text = "sec" 386 387 'Label7 388 389 Me.Label7.AutoSize = True 390 Me.Label7.Location = New System.Drawing.Point(95, 100) 391 Me.Label7.Name = "Label7" 392 Me.Label7.Size = New System.Drawing.Size(31, 15) Me.Label7.TabIndex = 23393 394 Me.Label7.Text = "1001"395 396 'halflife 397 398 Me.halflife.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), 399 CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer)) 400 Me.halflife.DecimalPlaces = 1 401 Me.halflife.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 402 CType(CType(255, Byte), Integer), CType(CType(192, Byte), Integer)) 403 Me.halflife.Increment = New Decimal(New Integer() {10, 0, 0, 0}) 404 Me.halflife.Location = New System.Drawing.Point(39, 38) 405 Me.halflife.Maximum = New Decimal(New Integer() {10000, 0, 0, 0}) 406 Me.halflife.Minimum = New Decimal(New Integer() {1, 0, 0, 0}) 407 Me.halflife.Name = "halflife" 408 Me.halflife.Size = New System.Drawing.Size(75, 23) 409 Me.halflife.TabIndex = 16410 Me.halflife.Value = New Decimal(New Integer() $\{5, 0, 0, 0\}$) 411 'Button5 412 413 414 Me.Button5.BackColor = System.Drawing.Color.Transparent 415 Me.Button5.FlatAppearance.MouseDownBackColor = System.Drawing.Color.FromArgb(CType(CType(64, 416 Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer)) 417 Me.Button5.FlatAppearance.MouseOverBackColor = System.Drawing.Color.FromArgb(CType(CType(64, 418 Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer)) 419 Me.Button5.FlatStyle = System.Windows.Forms.FlatStyle.Flat 420 Me.Button5.Location = New System.Drawing.Point(69, 98) 421 Me.Button5.Name = "Button5" 422 Me.Button5.Size = New System.Drawing.Size(20, 25) 423 Me.Button5.TabIndex = 19424 Me.Button5.Text = "4"425 Me.Button5.UseVisualStyleBackColor = False 426 427 'Label6 428 429 Me.Label6.AutoSize = True Me.Label6.Location = New System.Drawing.Point(95, 72) 430 431 Me.Label6.Name = "Label6" 432 Me.Label6.Size = New System.Drawing.Size(31, 15) 433 Me.Label6.TabIndex = 22434 Me.Label6.Text = "1100"435

```
436
           'Label10
437
438
           Me.Label10.AutoSize = True
439
           Me.Label10.Location = New System.Drawing.Point(116, 18)
440
           Me.Label10.Name = "Label10"
441
           Me.Label10.Size = New System.Drawing.Size(42, 15)
442
           Me.Label10.TabIndex = 15
443
           Me.Label10.Text = "ms/pin"
444
445
           'Label5
446
447
           Me.Label5.AutoSize = True
448
           Me.Label5.Location = New System.Drawing.Point(32, 101)
449
           Me.Label5.Name = "Label5"
450
           Me.Label5.Size = New System.Drawing.Size(31, 15)
451
           Me.Label5.TabIndex = 21
452
           Me.Label5.Text = "0110"
453
454
           'Button4
455
456
           Me.Button4.BackColor = System.Drawing.Color.Transparent
457
           Me.Button4.FlatAppearance.MouseDownBackColor = System.Drawing.Color.FromArgb(CType(CType(64,
458
      Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
459
           Me.Button4.FlatAppearance.MouseOverBackColor = System.Drawing.Color.FromArgb(CType(CType(64,
460
      Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
461
           Me.Button4.FlatStyle = System.Windows.Forms.FlatStyle.Flat
           Me.Button4.Location = New System.Drawing.Point(69, 68)
462
463
           Me.Button4.Name = "Button4"
464
           Me.Button4.Size = New System.Drawing.Size(20, 25)
465
           Me.Button4.TabIndex = 18
466
           Me.Button4.Text = "3"
467
           Me.Button4.UseVisualStyleBackColor = False
468
469
           'boxtimer
470
471
           Me.boxtimer.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer),
472
      CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
473
           Me.boxtimer.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer),
474
      CType(CType(255, Byte), Integer), CType(CType(192, Byte), Integer))
475
           Me.boxtimer.Increment = New Decimal(New Integer() \{5, 0, 0, 0\})
476
           Me.boxtimer.Location = New System.Drawing.Point(39, 16)
477
           Me.boxtimer.Maximum = New Decimal(New Integer() \{1000, 0, 0, 0\})
478
           Me.boxtimer.Minimum = New Decimal(New Integer() \{1, 0, 0, 0\})
479
           Me.boxtimer.Name = "boxtimer"
480
           Me.boxtimer.Size = New System.Drawing.Size(75, 23)
481
           Me.boxtimer.TabIndex = 13
482
           Me.boxtimer.Value = New Decimal(New Integer() {25, 0, 0, 0})
483
484
           'Label4
485
486
           Me.Label4.AutoSize = True
487
           Me.Label4.BackColor = System.Drawing.Color.Transparent
488
           Me.Label4.Location = New System.Drawing.Point(32, 72)
489
           Me.Label4.Name = "Label4"
490
           Me.Label4.Size = New System.Drawing.Size(31, 15)
491
           Me.Label4.TabIndex = 20
```

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492
           Me.Label4.Text = "0011"
493
494
           'Button3
495
496
           Me.Button3.BackColor = System.Drawing.Color.Transparent
497
           Me.Button3.FlatAppearance.MouseDownBackColor = System.Drawing.Color.FromArgb(CType(CType(64,
498
      Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
499
           Me.Button3.FlatAppearance.MouseOverBackColor = System.Drawing.Color.FromArgb(CType(CType(64,
500
      Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
501
           Me.Button3.FlatStyle = System.Windows.Forms.FlatStyle.Flat
502
           Me.Button3.Location = New System.Drawing.Point(6, 97)
503
           Me.Button3.Name = "Button3"
504
           Me.Button3.Size = New System.Drawing.Size(20, 25)
505
           Me.Button3.TabIndex = 17
506
           Me.Button3.Text = "2"
507
           Me.Button3.UseVisualStyleBackColor = False
508
509
           'Label2
510
511
           Me.Label2.AutoSize = True
512
           Me.Label2.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer),
513
      CType(CType(255, Byte), Integer), CType(CType(192, Byte), Integer))
514
           Me.Label2.Location = New System.Drawing.Point(0, 40)
515
           Me.Label2.Name = "Label2"
           Me.Label2.Size = New System.Drawing.Size(35, 15)
516
           Me.Label2.TabIndex = 11
517
518
           Me.Label2.Text = "T1/2:"
519
520
           'Button2
521
522
           Me.Button2.BackColor = System.Drawing.Color.Transparent
523
           Me.Button2.FlatAppearance.MouseDownBackColor = System.Drawing.Color.FromArgb(CType(CType(64,
524
      Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
525
           Me.Button2.FlatAppearance.MouseOverBackColor = System.Drawing.Color.FromArgb(CType(CType(64,
      Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
526
527
           Me.Button2.FlatStyle = System.Windows.Forms.FlatStyle.Flat
528
           Me.Button2.Location = New System.Drawing.Point(6, 67)
529
           Me.Button2.Name = "Button2"
530
           Me.Button2.Size = New System.Drawing.Size(20, 24)
531
           Me.Button2.TabIndex = 16
532
           Me.Button2.Text = "1"
           Me.Button2.UseVisualStyleBackColor = False
533
534
535
           'Label1
536
537
           Me.Label1.AutoSize = True
           Me.Label1.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer),
538
539
      CType(CType(255, Byte), Integer), CType(CType(192, Byte), Integer))
540
           Me.Label1.Location = New System.Drawing.Point(0, 21)
541
           Me.Label1.Name = "Label1"
542
           Me.Label1.Size = New System.Drawing.Size(33, 15)
543
           Me.Label1.TabIndex = 9
544
           Me.Label1.Text = "Rate:"
545
546
           'reset
547
```

```
548
           Me.reset.BackColor = System.Drawing.Color.Transparent
549
           Me.reset.FlatAppearance.MouseDownBackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte),
550
      Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
551
           Me.reset.FlatAppearance.MouseOverBackColor = System.Drawing.Color.FromArgb(CType(64, Byte),
552
      Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
553
           Me.reset.FlatStyle = System.Windows.Forms.FlatStyle.Flat
554
           Me.reset.ForeColor = System.Drawing.Color.Maroon
555
           Me.reset.Location = New System.Drawing.Point(39, 103)
556
           Me.reset.Name = "reset"
           Me.reset.Size = New System.Drawing.Size(45, 22)
557
           Me.reset.TabIndex = 14
558
559
           Me.reset.Text = "Reset"
560
           Me.reset.UseVisualStyleBackColor = False
561
562
           'stopbutton2
563
564
           Me.stopbutton2.BackColor = System.Drawing.Color.Transparent
565
           Me.stopbutton2.FlatAppearance.MouseDownBackColor =
566
      System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer),
567
      CType(CType(64, Byte), Integer))
           Me.stopbutton2.FlatAppearance.MouseOverBackColor = System.Drawing.Color.FromArgb(CType(CType(64,
568
569
      Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
570
           Me.stopbutton2.FlatStyle = System.Windows.Forms.FlatStyle.Flat
571
           Me.stopbutton2.Font = New System.Drawing.Font("Comic Sans MS", 8.25!,
572
      System.Drawing.FontStyle.Regular, System.Drawing.GraphicsUnit.Point, CType(0, Byte))
           Me.stopbutton2.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer),
573
574
      CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))
575
           Me.stopbutton2.Location = New System.Drawing.Point(72, 30)
576
           Me.stopbutton2.Name = "stopbutton2"
           Me.stopbutton2.Size = New System.Drawing.Size(58, 26)
577
578
           Me.stopbutton2.TabIndex = 10
579
           Me.stopbutton2.Text = "Stop"
580
           Me.stopbutton2.UseVisualStyleBackColor = False
581
582
           'GroupBox4
583
584
           Me.GroupBox4.BackColor = System.Drawing.Color.Transparent
585
           Me.GroupBox4.Controls.Add(Me.Label27)
586
           Me.GroupBox4.Controls.Add(Me.Label28)
587
           Me.GroupBox4.Controls.Add(Me.Label25)
           Me.GroupBox4.Controls.Add(Me.Label26)
588
           Me.GroupBox4.Controls.Add(Me.Label23)
589
590
           Me.GroupBox4.Controls.Add(Me.Label24)
591
           Me.GroupBox4.Controls.Add(Me.Label22)
592
           Me.GroupBox4.Controls.Add(Me.Label21)
593
           Me.GroupBox4.Controls.Add(Me.daq7)
594
           Me.GroupBox4.Controls.Add(Me.daq6)
595
           Me.GroupBox4.Controls.Add(Me.daq5)
596
           Me.GroupBox4.Controls.Add(Me.daq4)
597
           Me.GroupBox4.Controls.Add(Me.dag3)
598
           Me.GroupBox4.Controls.Add(Me.daq2)
599
           Me.GroupBox4.Controls.Add(Me.dag1)
600
           Me.GroupBox4.Controls.Add(Me.daq0)
601
           Me.GroupBox4.Controls.Add(Me.dagenable)
602
           Me.GroupBox4.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
```

603 CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))

```
604
           Me.GroupBox4.Location = New System.Drawing.Point(321, 114)
605
           Me.GroupBox4.Name = "GroupBox4"
           Me.GroupBox4.Size = New System.Drawing.Size(398, 92)
606
607
           Me.GroupBox4.TabIndex = 31
608
           Me.GroupBox4.TabStop = False
609
           Me.GroupBox4.Text = "Real Time D.A.Q"
610
611
           'Label27
612
613
           Me.Label27.AutoSize = True
614
           Me.Label27.Location = New System.Drawing.Point(286, 66)
615
           Me.Label27.Name = "Label27"
616
           Me.Label27.Size = New System.Drawing.Size(29, 13)
617
           Me.Label27.TabIndex = 42
618
           Me.Label27.Text = "Ch7:"
619
620
           'Label28
621
622
           Me.Label28.AutoSize = True
623
           Me.Label28.Location = New System.Drawing.Point(286, 44)
624
           Me.Label28.Name = "Label28"
625
           Me.Label28.Size = New System.Drawing.Size(29, 13)
626
           Me.Label28.TabIndex = 41
627
           Me.Label28.Text = "Ch6:"
628
629
           'Label25
630
631
           Me.Label25.AutoSize = True
632
           Me.Label25.Location = New System.Drawing.Point(194, 66)
633
           Me.Label25.Name = "Label25"
634
           Me.Label25.Size = New System.Drawing.Size(29, 13)
635
           Me.Label25.TabIndex = 40
636
           Me.Label25.Text = "Ch5:"
637
638
           'Label26
639
640
           Me.Label26.AutoSize = True
641
           Me.Label26.Location = New System.Drawing.Point(194, 44)
642
           Me.Label26.Name = "Label26"
643
           Me.Label26.Size = New System.Drawing.Size(29, 13)
644
           Me.Label26.TabIndex = 39
645
           Me.Label26.Text = "Ch4:"
646
647
           'Label23
648
649
           Me.Label23.AutoSize = True
650
           Me.Label23.Location = New System.Drawing.Point(102, 65)
651
           Me.Label23.Name = "Label23"
652
           Me.Label23.Size = New System.Drawing.Size(29, 13)
653
           Me.Label23.TabIndex = 38
654
           Me.Label23.Text = "Ch3:"
655
656
           'Label24
657
658
           Me.Label24.AutoSize = True
659
           Me.Label24.Location = New System.Drawing.Point(102, 43)
```

```
660
           Me.Label24.Name = "Label24"
           Me.Label24.Size = New System.Drawing.Size(29, 13)
661
662
           Me.Label24.TabIndex = 37
663
           Me.Label24.Text = "Ch2:"
664
665
           'Label22
666
667
           Me.Label22.AutoSize = True
           Me.Label22.Location = New System.Drawing.Point(11, 66)
668
           Me.Label22.Name = "Label22"
669
670
           Me.Label22.Size = New System.Drawing.Size(29, 13)
671
           Me.Label22.TabIndex = 36
672
           Me.Label22.Text = "Ch1:"
673
674
           'Label21
675
676
           Me.Label21.AutoSize = True
677
           Me.Label21.Location = New System.Drawing.Point(9, 44)
           Me.Label21.Name = "Label21"
678
679
           Me.Label21.Size = New System.Drawing.Size(29, 13)
680
           Me.Label21.TabIndex = 35
           Me.Label21.Text = "Ch0:"
681
682
683
           'daq7
684
           Me.daq7.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64,
685
686
      Byte), Integer), CType(CType(64, Byte), Integer))
           Me.daq7.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
687
688
      CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))
           Me.daq7.Location = New System.Drawing.Point(316, 62)
689
690
           Me.daq7.Name = "daq7"
691
           Me.daq7.Size = New System.Drawing.Size(62, 20)
692
           Me.daq7.TabIndex = 34
693
694
           'daq6
695
696
           Me.daq6.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64,
      Byte), Integer), CType(CType(64, Byte), Integer))
697
698
           Me.daq6.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
699
      CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))
700
           Me.daq6.Location = New System.Drawing.Point(316, 40)
701
           Me.daq6.Name = "daq6"
702
           Me.daq6.Size = New System.Drawing.Size(62, 20)
703
           Me.daq6.TabIndex = 33
704
705
           'daq5
706
707
           Me.daq5.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64,
708
      Byte), Integer), CType(CType(64, Byte), Integer))
709
           Me.daq5.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
710
      CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))
711
           Me.daq5.Location = New System.Drawing.Point(224, 62)
712
           Me.daq5.Name = "daq5"
713
           Me.daq5.Size = New System.Drawing.Size(62, 20)
714
           Me.daq5.TabIndex = 32
```

715

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716
           'daq4
717
718
           Me.daq4.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64,
719
      Byte), Integer), CType(CType(64, Byte), Integer))
720
           Me.daq4.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
721
      CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))
722
           Me.daq4.Location = New System.Drawing.Point(224, 40)
723
           Me.daq4.Name = "daq4"
724
           Me.daq4.Size = New System.Drawing.Size(62, 20)
           Me.daq4.TabIndex = 31
725
726
727
           'dag3
728
729
           Me.daq3.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64,
730
      Byte), Integer), CType(CType(64, Byte), Integer))
731
           Me.daq3.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
732
      CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))
733
           Me.daq3.Location = New System.Drawing.Point(132, 62)
734
           Me.daq3.Name = "daq3"
735
           Me.daq3.Size = New System.Drawing.Size(62, 20)
736
           Me.daq3.TabIndex = 30
737
738
           'daq2
739
740
           Me.daq2.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64,
741
      Byte), Integer), CType(CType(64, Byte), Integer))
742
           Me.daq2.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
743
      CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))
744
           Me.daq2.Location = New System.Drawing.Point(132, 40)
745
           Me.daq2.Name = "daq2"
746
           Me.daq2.Size = New System.Drawing.Size(62, 20)
747
           Me.daq2.TabIndex = 29
748
749
           'daq1
750
751
           Me.daq1.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64,
752
      Byte), Integer), CType(CType(64, Byte), Integer))
753
           Me.daq1.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
754
      CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))
           Me.daq1.Location = New System.Drawing.Point(40, 62)
755
756
           Me.daq1.Name = "daq1"
757
           Me.daq1.Size = New System.Drawing.Size(62, 20)
758
           Me.daq1.TabIndex = 28
759
760
           'daq0
761
762
           Me.daq0.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64,
763
      Byte), Integer), CType(CType(64, Byte), Integer))
764
           Me.daq0.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
765
      CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer))
766
           Me.daq0.Location = New System.Drawing.Point(40, 40)
767
           Me.daq0.Name = "daq0"
768
           Me.daq0.Size = New System.Drawing.Size(62, 20)
769
           Me.daq0.TabIndex = 27
770
771
           'daqenable
```

```
772
773
           Me.daqenable.AutoSize = True
774
           Me.dagenable.Checked = True
775
           Me.dagenable.CheckState = System.Windows.Forms.CheckState.Checked
776
           Me.daqenable.Location = New System.Drawing.Point(6, 18)
777
           Me.daqenable.Name = "daqenable"
778
           Me.daqenable.Size = New System.Drawing.Size(276, 17)
779
           Me.dagenable.TabIndex = 0
780
           Me.dagenable.Text = "Enable Real Time D.A.Q. (Slows down performance!)"
781
           Me.daqenable.UseVisualStyleBackColor = True
782
783
           'TextBox2
784
785
           Me.TextBox2.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer),
786
      CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
787
           Me.TextBox2.BorderStyle = System.Windows.Forms.BorderStyle.None
788
           Me.TextBox2.Font = New System.Drawing.Font("Comic Sans MS", 8.25!, System.Drawing.FontStyle.Bold,
789
      System.Drawing.GraphicsUnit.Point, CType(0, Byte))
790
           Me.TextBox2.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
791
      CType(CType(255, Byte), Integer), CType(CType(192, Byte), Integer))
792
           Me.TextBox2.Location = New System.Drawing.Point(5, 306)
793
           Me.TextBox2.Name = "TextBox2"
794
           Me.TextBox2.Size = New System.Drawing.Size(711, 16)
795
           Me.TextBox2.TabIndex = 30
796
           Me.TextBox2.Text = "Chnnl: Signal / Time.Stmp / Event#"
797
798
           'TextBox1
799
800
           Me.TextBox1.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer),
801
      CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
802
           Me.TextBox1.BorderStyle = System.Windows.Forms.BorderStyle.None
803
           Me.TextBox1.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
804
      CType(CType(255, Byte), Integer), CType(CType(192, Byte), Integer))
805
           Me.TextBox1.Location = New System.Drawing.Point(5, 322)
806
           Me.TextBox1.Multiline = True
807
           Me.TextBox1.Name = "TextBox1"
808
           Me.TextBox1.ScrollBars = System.Windows.Forms.ScrollBars.Vertical
809
           Me.TextBox1.Size = New System.Drawing.Size(711, 389)
810
           Me.TextBox1.TabIndex = 29
811
812
           'GroupBox3
813
814
           Me.GroupBox3.BackColor = System.Drawing.Color.Transparent
815
           Me.GroupBox3.Controls.Add(Me.Label17)
816
           Me.GroupBox3.Controls.Add(Me.Labelbarstep)
           Me.GroupBox3.Controls.Add(Me.barstep)
817
818
           Me.GroupBox3.Controls.Add(Me.Label16)
819
           Me.GroupBox3.Controls.Add(Me.Label15)
820
           Me.GroupBox3.Controls.Add(Me.Labelbarfull)
821
           Me.GroupBox3.Controls.Add(Me.boxcomfull)
822
           Me.GroupBox3.Controls.Add(Me.Label14)
823
           Me.GroupBox3.Controls.Add(Me.Label13)
824
           Me.GroupBox3.Controls.Add(Me.barfull)
825
           Me.GroupBox3.Controls.Add(Me.Button6)
826
           Me.GroupBox3.Controls.Add(Me.boxtfire)
827
           Me.GroupBox3.Controls.Add(Me.Label9)
```

```
828
           Me.GroupBox3.Controls.Add(Me.boxport)
829
           Me.GroupBox3.Controls.Add(Me.Label8)
830
           Me.GroupBox3.Font = New System.Drawing.Font("Comic Sans MS", 8.25!,
831
      System.Drawing.FontStyle.Regular, System.Drawing.GraphicsUnit.Point, CType(0, Byte))
832
           Me.GroupBox3.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
833
      CType(CType(224, Byte), Integer), CType(CType(192, Byte), Integer))
834
           Me.GroupBox3.Location = New System.Drawing.Point(8, 166)
835
           Me.GroupBox3.Name = "GroupBox3"
836
           Me.GroupBox3.Size = New System.Drawing.Size(307, 117)
837
           Me.GroupBox3.TabIndex = 28
838
           Me.GroupBox3.TabStop = False
839
           Me.GroupBox3.Text = "Stepper Diagnostics"
840
841
           'Label17
842
843
           Me.Label17.AutoSize = True
844
           Me.Label17.Location = New System.Drawing.Point(279, 42)
845
           Me.Label17.Name = "Label17"
           Me.Label17.Size = New System.Drawing.Size(16, 15)
846
847
           Me.Label17.TabIndex = 14
848
           Me.Label17.Text = "%"
849
850
           'Labelbarstep
851
           Me.Labelbarstep.AutoSize = True
852
853
           Me.Labelbarstep.Location = New System.Drawing.Point(253, 42)
854
           Me.Labelbarstep.Name = "Labelbarstep"
855
           Me.Labelbarstep.Size = New System.Drawing.Size(31, 15)
856
           Me.Labelbarstep.TabIndex = 13
857
           Me.Labelbarstep.Text = "00.0"
858
859
           'barstep
860
861
           Me.barstep.BackColor = System.Drawing.Color.Black
862
           Me.barstep.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
863
      CType(CType(224, Byte), Integer), CType(CType(192, Byte), Integer))
864
           Me.barstep.Location = New System.Drawing.Point(144, 42)
865
           Me.barstep.Maximum = 51
866
           Me.barstep.Name = "barstep"
867
           Me.barstep.Size = New System.Drawing.Size(103, 13)
868
           Me.barstep.TabIndex = 12
869
870
           'Label16
871
872
           Me.Label16.AutoSize = True
873
           Me.Label16.Location = New System.Drawing.Point(0, 40)
874
           Me.Label16.Name = "Label16"
875
           Me.Label16.Size = New System.Drawing.Size(138, 15)
876
           Me.Label16.TabIndex = 11
           Me.Label16.Text = "Quarter Step Completion:"
877
878
879
           'Label15
880
881
           Me.Label15.AutoSize = True
882
           Me.Label15.Location = New System.Drawing.Point(279, 21)
883
           Me.Label15.Name = "Label15"
```

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884
           Me.Label15.Size = New System.Drawing.Size(16, 15)
           Me.Label15.TabIndex = 10
885
886
           Me.Label15.Text = "%"
887
888
           'Labelbarfull
889
890
           Me.Labelbarfull.AutoSize = True
891
           Me.Labelbarfull.Location = New System.Drawing.Point(253, 21)
892
           Me.Labelbarfull.Name = "Labelbarfull"
893
           Me.Labelbarfull.Size = New System.Drawing.Size(31, 15)
           Me.Labelbarfull.TabIndex = 9
894
895
           Me.Labelbarfull.Text = "00.0"
896
897
           'boxcomfull
898
899
           Me.boxcomfull.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer),
900
      CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
901
           Me.boxcomfull.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
902
      CType(CType(224, Byte), Integer), CType(CType(192, Byte), Integer))
903
           Me.boxcomfull.Location = New System.Drawing.Point(126, 61)
904
           Me.boxcomfull.Name = "boxcomfull"
905
           Me.boxcomfull.Size = New System.Drawing.Size(35, 23)
906
           Me.boxcomfull.TabIndex = 8
907
           Me.boxcomfull.Text = "0"
908
909
           'Label14
910
911
           Me.Label14.AutoSize = True
912
           Me.Label14.Location = New System.Drawing.Point(7, 64)
913
           Me.Label14.Name = "Label14"
914
           Me.Label14.Size = New System.Drawing.Size(113, 15)
           Me.Label14.TabIndex = 7
915
916
           Me.Label14.Text = "Completed Rotations:"
917
           'Label13
918
919
920
           Me.Label13.AutoSize = True
921
           Me.Label13.Location = New System.Drawing.Point(9, 19)
922
           Me.Label13.Name = "Label13"
923
           Me.Label13.Size = New System.Drawing.Size(129, 15)
924
           Me.Label13.TabIndex = 6
925
           Me.Label13.Text = "Full Rotaion Completion:"
926
927
           'barfull
928
929
           Me.barfull.BackColor = System.Drawing.Color.Black
930
           Me.barfull.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
931
      CType(CType(224, Byte), Integer), CType(CType(192, Byte), Integer))
932
           Me.barfull.Location = New System.Drawing.Point(144, 22)
933
           Me.barfull.Maximum = 200
           Me.barfull.Name = "barfull"
934
935
           Me.barfull.Size = New System.Drawing.Size(103, 14)
936
           Me.barfull.Step = 1
937
           Me.barfull.TabIndex = 5
938
939
           'Button6
```

```
940
941
           Me.Button6.FlatAppearance.MouseDownBackColor = System.Drawing.Color.FromArgb(CType(CType(64,
942
      Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
943
           Me.Button6.FlatAppearance.MouseOverBackColor = System.Drawing.Color.FromArgb(CType(CType(64, 
944
      Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
945
           Me.Button6.FlatStyle = System.Windows.Forms.FlatStyle.Flat
946
           Me.Button6.ForeColor = System.Drawing.Color.Maroon
947
           Me.Button6.Location = New System.Drawing.Point(167, 88)
948
           Me.Button6.Name = "Button6"
949
           Me.Button6.Size = New System.Drawing.Size(134, 22)
950
           Me.Button6.TabIndex = 4
951
           Me.Button6.Text = "Reset"
952
           Me.Button6.UseVisualStyleBackColor = True
953
954
           'boxtfire
955
956
           Me.boxtfire.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer),
957
      CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
958
           Me.boxtfire.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
959
      CType(CType(224, Byte), Integer), CType(CType(192, Byte), Integer))
960
           Me.boxtfire.Location = New System.Drawing.Point(126, 85)
           Me.boxtfire.Name = "boxtfire"
961
962
           Me.boxtfire.Size = New System.Drawing.Size(35, 23)
963
           Me.boxtfire.TabIndex = 3
964
           Me.boxtfire.Text = "0"
965
966
           'Label9
967
968
           Me.Label9.AutoSize = True
969
           Me.Label9.Location = New System.Drawing.Point(54, 88)
970
           Me.Label9.Name = "Label9"
971
           Me.Label9.Size = New System.Drawing.Size(66, 15)
972
           Me.Label9.TabIndex = 2
           Me.Label9.Text = "Total Fired:"
973
974
975
           'boxport
976
977
           Me.boxport.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer),
978
      CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer))
979
           Me.boxport.ForeColor = System.Drawing.Color.FromArgb(CType(CType(255, Byte), Integer),
980
      CType(CType(224, Byte), Integer), CType(CType(192, Byte), Integer))
981
           Me.boxport.Location = New System.Drawing.Point(238, 61)
982
           Me.boxport.Name = "boxport"
983
           Me.boxport.Size = New System.Drawing.Size(35, 23)
984
           Me.boxport.TabIndex = 1
985
           Me.boxport.Text = "null"
986
987
           'Label8
988
989
           Me.Label8.AutoSize = True
990
           Me.Label8.Location = New System.Drawing.Point(167, 64)
991
           Me.Label8.Name = "Label8"
992
           Me.Label8.Size = New System.Drawing.Size(65, 15)
993
           Me.Label8.TabIndex = 0
994
           Me.Label8.Text = "Port Firing:"
995
```

996 'Timer1 997 998 Me.Timer1.Interval = 1999 1000 'timerstep 1001 1002 1003 'Button1 1004 Me.Button1.BackColor = System.Drawing.Color.Transparent 1005 Me.Button1.FlatAppearance.MouseDownBackColor = System.Drawing.Color.FromArgb(CType(CType(64, 1006 1007 Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer)) 1008 Me.Button1.FlatAppearance.MouseOverBackColor = System.Drawing.Color.FromArgb(CType(CType(64, 1009 Byte), Integer), CType(CType(64, Byte), Integer), CType(CType(64, Byte), Integer)) 1010 Me.Button1.FlatStyle = System.Windows.Forms.FlatStyle.Flat 1011 Me.Button1.Font = New System.Drawing.Font("Comic Sans MS", 8.25!, System.Drawing.FontStyle.Regular, 1012 System.Drawing.GraphicsUnit.Point, CType(0, Byte)) Me.Button1.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 1013 CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer)) 1014 1015 Me.Button1.Location = New System.Drawing.Point(9, 30) 1016 Me.Button1.Name = "Button1" 1017 Me.Button1.Size = New System.Drawing.Size(58, 26) 1018 Me.Button1.TabIndex = 81019 Me.Button1.Text = "Start" Me.Button1.UseVisualStyleBackColor = False 1020 1021 1022 'MasterControls 1023 1024 Me.MasterControls.BackColor = System.Drawing.Color.Transparent 1025 Me.MasterControls.Controls.Add(Me.Button1) 1026 Me.MasterControls.Controls.Add(Me.stopbutton2) Me.MasterControls.Controls.Add(Me.reset) 1027 Me.MasterControls.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 1028 1029 CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer)) 1030 Me.MasterControls.Location = New System.Drawing.Point(176, 28) 1031 Me.MasterControls.Name = "MasterControls" 1032 Me.MasterControls.Size = New System.Drawing.Size(139, 133) 1033 Me.MasterControls.TabIndex = 32 1034 Me.MasterControls.TabStop = False 1035 Me.MasterControls.Text = "Run Controls" 1036 1037 'MenuStrip1 1038 1039 Me.MenuStrip1.BackColor = System.Drawing.Color.Transparent 1040 Me.MenuStrip1.Font = New System.Drawing.Font("Comic Sans MS", 8.25!, System.Drawing.FontStyle.Regular, System.Drawing.GraphicsUnit.Point, CType(0, Byte)) 1041 1042 Me.MenuStrip1.Items.AddRange(New System.Windows.Forms.ToolStripItem() 1043 {Me.HelpToolStripMenuItem}) 1044 Me.MenuStrip1.Location = New System.Drawing.Point(0, 0) 1045 Me.MenuStrip1.Name = "MenuStrip1" 1046 Me.MenuStrip1.Size = New System.Drawing.Size(728, 24) 1047 Me.MenuStrip1.TabIndex = 331048 Me.MenuStrip1.Text = "MenuStrip1" 1049 1050 'HelpToolStripMenuItem 1051

1052 Me.HelpToolStripMenuItem.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), 1053 Integer), CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer)) 1054 Me.HelpToolStripMenuItem.Name = "HelpToolStripMenuItem" 1055 Me.HelpToolStripMenuItem.Size = New System.Drawing.Size(42, 20) 1056 Me.HelpToolStripMenuItem.Text = "Help" 1057 1058 'samples100 1059 1060 'bit0CheckBox 1061 1062 1063 Me.bit0CheckBox.AutoSize = True 1064 Me.bit0CheckBox.BackColor = System.Drawing.Color.Transparent 1065 Me.bit0CheckBox.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 1066 CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer)) 1067 Me.bit0CheckBox.Location = New System.Drawing.Point(76, 53) Me.bit0CheckBox.Name = "bit0CheckBox" 1068 Me.bit0CheckBox.Size = New System.Drawing.Size(33, 19) 1069 1070 Me.bit0CheckBox.TabIndex = 35 Me.bit0CheckBox.Text = "0" 1071 1072 Me.bit0CheckBox.UseVisualStyleBackColor = False 1073 1074 'bit1CheckBox 1075 1076 Me.bit1CheckBox.AutoSize = True Me.bit1CheckBox.BackColor = System.Drawing.Color.Transparent 1077 Me.bit1CheckBox.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 1078 CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer)) 1079 Me.bit1CheckBox.Location = New System.Drawing.Point(105, 53) 1080 Me.bit1CheckBox.Name = "bit1CheckBox" 1081 1082 Me.bit1CheckBox.Size = New System.Drawing.Size(31, 19) 1083 Me.bit1CheckBox.TabIndex = 36 Me.bit1CheckBox.Text = "1" 1084 1085 Me.bit1CheckBox.UseVisualStyleBackColor = False 1086 1087 'bit2CheckBox 1088 1089 Me.bit2CheckBox.AutoSize = True 1090 Me.bit2CheckBox.BackColor = System.Drawing.Color.Transparent 1091 Me.bit2CheckBox.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer)) 1092 Me.bit2CheckBox.Location = New System.Drawing.Point(132, 53) 1093 Me.bit2CheckBox.Name = "bit2CheckBox" 1094 1095 Me.bit2CheckBox.Size = New System.Drawing.Size(33, 19) 1096 Me.bit2CheckBox.TabIndex = 37 Me.bit2CheckBox.Text = "2" 1097 Me.bit2CheckBox.UseVisualStyleBackColor = False 1098 1099 'bit3CheckBox 1100 1101 1102 Me.bit3CheckBox.AutoSize = True 1103 Me.bit3CheckBox.BackColor = System.Drawing.Color.Transparent 1104 Me.bit3CheckBox.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 1105 CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer)) 1106 Me.bit3CheckBox.Location = New System.Drawing.Point(161, 53)

1107 Me.bit3CheckBox.Name = "bit3CheckBox"

1108 Me.bit3CheckBox.Size = New System.Drawing.Size(33, 19) 1109 Me.bit3CheckBox.TabIndex = 38 Me.bit3CheckBox.Text = "3" 1110 1111 Me.bit3CheckBox.UseVisualStyleBackColor = False 1112 1113 'bit4CheckBox 1114 1115 Me.bit4CheckBox.AutoSize = True Me.bit4CheckBox.BackColor = System.Drawing.Color.Transparent 1116 Me.bit4CheckBox.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 1117 CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer)) 1118 1119 Me.bit4CheckBox.Location = New System.Drawing.Point(190, 53) Me.bit4CheckBox.Name = "bit4CheckBox" 1120 1121 Me.bit4CheckBox.Size = New System.Drawing.Size(33, 19) 1122 Me.bit4CheckBox.TabIndex = 39 1123 Me.bit4CheckBox.Text = "4" Me.bit4CheckBox.UseVisualStyleBackColor = False 1124 1125 1126 'bit5CheckBox 1127 1128 Me.bit5CheckBox.AutoSize = True Me.bit5CheckBox.BackColor = System.Drawing.Color.Transparent 1129 Me.bit5CheckBox.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 1130 1131 CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer)) Me.bit5CheckBox.Location = New System.Drawing.Point(219, 53) 1132 Me.bit5CheckBox.Name = "bit5CheckBox" 1133 Me.bit5CheckBox.Size = New System.Drawing.Size(33, 19) 1134 1135 Me.bit5CheckBox.TabIndex = 401136 Me.bit5CheckBox.Text = "5" Me.bit5CheckBox.UseVisualStyleBackColor = False 1137 1138 1139 'bit6CheckBox 1140 1141 Me.bit6CheckBox.AutoSize = True 1142 Me.bit6CheckBox.BackColor = System.Drawing.Color.Transparent 1143 Me.bit6CheckBox.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 1144 CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer)) 1145 Me.bit6CheckBox.Location = New System.Drawing.Point(250, 53) 1146 Me.bit6CheckBox.Name = "bit6CheckBox" 1147 Me.bit6CheckBox.Size = New System.Drawing.Size(33, 19) Me.bit6CheckBox.TabIndex = 411148 1149 Me.bit6CheckBox.Text = "6"Me.bit6CheckBox.UseVisualStyleBackColor = False 1150 1151 1152 'bit7CheckBox 1153 Me.bit7CheckBox.AutoSize = True 1154 Me.bit7CheckBox.BackColor = System.Drawing.Color.Transparent 1155 Me.bit7CheckBox.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer), 1156 CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer)) 1157 1158 Me.bit7CheckBox.Location = New System.Drawing.Point(279, 53) 1159 Me.bit7CheckBox.Name = "bit7CheckBox" Me.bit7CheckBox.Size = New System.Drawing.Size(33, 19) 1160 Me.bit7CheckBox.TabIndex = 421161 Me.bit7CheckBox.Text = "7" 1162

1163 Me.bit7CheckBox.UseVisualStyleBackColor = False

1164	· · · · · · · · · · · · · · · · · · ·
1165	writeDutton
1105	
1100	Manuita Duttan Daak Calan Gustan Drawing Calan Diach
110/	Me.whiteDutton Electrola System Windows Electrola Elect
1168	Me.writeButton.FlatStyle = System.windows.Forms.FlatStyle.Flat
1169	Me.writeButton.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer),
1170	CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer))
1171	Me.writeButton.Location = New System.Drawing.Point(14, 46)
1172	Me.writeButton.Name = "writeButton"
1173	Me.writeButton.Size = New System.Drawing.Size(55, 23)
1174	Me.writeButton.TabIndex = 43
1175	Me.writeButton.Text = "DI Out"
1176	Me.writeButton.UseVisualStyleBackColor = False
1177	,
1178	'rstckbx
1179	,
1180	Me.rstckbx.AutoSize = True
1181	Me.rstckbx.BackColor = System.Drawing.Color.Transparent
1182	Me.rstckbx.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer),
1183	CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer))
1184	Me.rstckbx.Location = New System.Drawing.Point(311, 53)
1185	Me.rstckbx.Name = "rstckbx"
1186	Me.rstckbx.Size = New System.Drawing.Size(31, 19)
1187	Me.rstckbx.TabIndex = 44
1188	Me.rstckbx.Text = " r "
1189	Me.rstckbx.UseVisualStyleBackColor = False
1190	
1191	'GroupBox1
1192	
1193	Me.GroupBox1.BackColor = System.Drawing.Color.Transparent
1194	Me.GroupBox1.Controls.Add(Me.beam)
1195	Me. GroupBox1. Controls. Add(Me. thfilename)
1196	Me.GroupBox1.Controls.Add(Me.rstckbx)
1197	Me. GroupBox1. Controls. Add(Me. writeButton)
1198	Me. GroupBox1. Controls. Add(Me. bit0CheckBox)
1199	Me. GroupBox1. Controls. Add(Me. bit7CheckBox)
1200	Me GroupBox1 Controls Add(Me bit1CheckBox)
1201	Me GroupBox1 Controls Add(Me bit6CheckBox)
1202	Me GroupBox1 Controls Add(Me bit2CheckBox)
1202	Me. GroupBox1. Controls. Add(Me.bit5CheckBox)
1204	Me GroupBox1 Controls Add(Me bit3CheckBox)
1205	Me GroupBox1 Controls Add(Me bit4CheckBox)
1205	Me GroupBox1 Font = New System Drawing Font("Comic Sans MS" 8 25!
1200	System Drawing FontStyle Regular System Drawing GraphicsUnit Point (Type(0, Byte))
1207	Me GroupBox1 ForeColor = System Drawing Color From Argh(CType(CType(192 Byte)) Integer)
1200	CType(CType(255 Byte) Integer) CType(CType(255 Byte) Integer))
1210	Me GroupBox1 Location - New System Drawing Point(321, 208)
1210	Me GroupBox1 Name = "GroupBox1"
1211	Me GroupBox1 Size = New System Drawing Size(395–75)
1212	Me.GroupBox1.5hz = 46
1213	Me GroupBox1 TabStop - False
1214	Me GroupBox1 Text - "File Name and Digital Resets"
1215	
1210	'thfilename
1217	tomonamo
1210	Me thfilename BackColor - System Drawing Color Plack
1417	Monomenanc. DackColor – System. Drawing. Color. Diack

1220	Me.tbfilename.BorderStyle = System.Windows.Forms.BorderStyle.None
1221	Me.tbfilename.Font = New System.Drawing.Font("Comic Sans MS", 8.25!,
1222	System.Drawing.FontStyle.Regular, System.Drawing.GraphicsUnit.Point, CType(0, Byte))
1223	Me.tbfilename.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer),
1224	CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer))
1225	Me.tbfilename.Location = New System.Drawing.Point(14, 19)
1226	Me.tbfilename.Name = "tbfilename"
1227	Me.tbfilename.Size = New System.Drawing.Size(298, 16)
1228	Me.tbfilename.TabIndex = 45
1229	Me.tbfilename.Text = "C:\Documents and Settings\Mitch\Desktop\data0.txt"
1230	
1231	'beam
1232	·
1233	Me.beam.BackColor = System.Drawing.Color.FromArgb(CType(CType(64, Byte), Integer), CType(CType(64,
1234	Byte), Integer), CType(CType(64, Byte), Integer))
1235	Me.beam.ForeColor = System.Drawing.Color.FromArgb(CType(CType(192, Byte), Integer),
1236	CType(CType(255, Byte), Integer), CType(CType(255, Byte), Integer))
1237	Me.beam.Location = New System.Drawing.Point(318, 17)
1238	Me.beam.Name = "beam"
1239	Me.beam.Size = New System.Drawing.Size(69, 23)
1240	Me.beam.TabIndex = 47
1241	•
1242	'MainForm
1243	·
1244	Me.AutoScaleBaseSize = New System.Drawing.Size(5, 13)
1245	Me.BackgroundImage = CType(resources.GetObject("\$this.BackgroundImage"), System.Drawing.Image)
1246	Me.ClientSize = New System.Drawing.Size(728, 714)
1247	Me.Controls.Add(Me.GroupBox1)
1248	Me.Controls.Add(Me.MasterControls)
1249	Me.Controls.Add(Me.GroupBox4)
1250	Me.Controls.Add(Me.runcontrols)
1251	Me.Controls.Add(Me.TextBox2)
1252	Me.Controls.Add(Me.TextBox1)
1253	Me.Controls.Add(Me.GroupBox3)
1254	Me.Controls.Add(Me.channelParametersGroupBox)
1255	Me.Controls.Add(Me.MenuStrip1)
1256	Me.FormBorderStyle = System.Windows.Forms.FormBorderStyle.FixedDialog
1257	Me.Icon = CType(resources.GetObject("\$this.Icon"), System.Drawing.Icon)
1258	Me.MainMenuStrip = Me.MenuStrip1
1259	Me.MaximumSize = New System.Drawing.Size(2560, 4560)
1260	Me.MinimumSize = New System.Drawing.Size(256, 320)
1261	Me.Name = "MainForm"
1262	Me.StartPosition = System.Windows.FormS.FormStartPosition.CenterScreen
1263	Me.Text = " [*] "
1264	Me.channelParametersGroupBox.ResumeLayout(False)
1265	Me.channelParametersGroupBox.PerformLayout()
1266	CType(Me.threshold, System.ComponentModel.ISupportInitialize).EndInit()
1267	CType(Me.minimumValueNumeric, System.ComponentModel.ISupportInitialize).EndInit()
1268	CType(Me.maximumValueNumeric, System.ComponentModel.ISupportInitialize).EndInit()
1269	Me.runcontrols.ResumeLayout(False)
1270	Me.runcontrols.PerformLayout()
1271	CType(Me.halflife, System.ComponentModel.ISupportInitialize).EndInit()
1272	CType(Me.boxtimer, System.ComponentModel.ISupportInitialize).EndInit()
1273	Me.GroupBox4.ResumeLayout(False)
1274	Me.GroupBox4.PerformLayout()
1275	Me.GroupBox3.ResumeLayout(False)

1276	Me.GroupBox3.PerformLayout()
1277	Me.MasterControls.ResumeLayout(False)
1278	Me.MenuStrip1.ResumeLayout(False)
1279	Me.MenuStrip1.PerformLayout()
1280	Me.GroupBox1.ResumeLayout(False)
1281	Me.GroupBox1.PerformLayout()
1282	Me.ResumeLayout(False)
1283	Me Perform Layout()
1200	
1284	End Sub
1285	#End Region
1286	Private Sub loopTimer_Tick(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles
1287	loop limer. lick
1288	Tru
1280	Presed one point of data per channel during every execution of the while loop
1209	Dim data() As Double = reader PeadSingleSemple()
1290	Dim data() As Double = reader.ReadSingleSample()
1291	time = My.Computer.Clock.TickCount
1292	'Plot your data here
1293	If dagenable Checked = True Then
1294	'dataToDataTable(data_dataTable)
1271	
1295	daq0.Text = data(0)
1296	daq1.Text = data(1)
1297	daq2.Text = data(2)
1298	$\frac{1}{2}$
1299	daq4 Text – $data(4)$
1200	daq = 1000
1300	daq 5.1ext - data(5)
1202	daq0.1ext = data(0)
1202	daq/.lext = data(/)
1505	
1304	If $data(0) > threshold. Value Then$
1305	TextBox1 AppendText(" 0: "& " "& Format(data(0) "0.0000") & " "& time & " "&
1306	(eventnumber ± 0) & vbCrI f)
1307	TextBox1 ScrollToCaret()
1507	
1308	PrintLine(1, "0: " & " " & data(0) & " " & time & " " & (eventnumber + 0))
1309	hit0CheckBox.Checked = True
1507	
1310	End If
1311	
1312	'If data(3) > 1 And beamstate = 0 Then
1313	'beam.Text = "beam on"
1314	TextBox1.AppendText("beam-on " & " " & time & vbCrLf)
1315	'PrintLine(1, "beam-on" & " " & time)
1316	beamstate = 1
1317	'End If
1017	
1318	'If data(3) < 1 And beamstate = 1 Then
1319	'beam.Text = "beam on"

1320 1321	'TextBox1.AppendText("beam-off " & " " & time & vbCrLf) 'PrintLine(1, "beam-off" & " " & time)
1322	beamstate = 0
1323	'End If
1324	If bit0CheckBox.Checked = True Or bit1CheckBox.Checked = True Or bit2CheckBox.Checked = True Then
1325	'Digital Resets below
1326	System.Windows.Forms.Cursor.Current = Cursors.WaitCursor
1327	Dim digitalWriteTask As Task = Nothing
1328	Try
1329	digitalWriteTask = New Task()
1330	digitalWriteTask.DOChannels.CreateChannel("Dev1/Port0/line0:7", "port0", _
1331	ChannelLineGrouping.OneChannelForAllLines)
1332	Dim dataArray(7) As Boolean
1333	CheckLines(dataArray)
1334	Dim writer As New DigitalSingleChannelWriter(digitalWriteTask.Stream)
1335	writer.WriteSingleSampleMultiLine(True, dataArray)
1336	Catch exception As DaqException
1337	MessageBox.Show(exception.Message)
1338	Finally
1339	digitalWriteTask.Dispose()
1340	System.Windows.Forms.Cursor.Current = Cursors.Default
1341	End Try
1342	bit0CheckBox.Checked = False
1343	bit1CheckBox.Checked = False
1344	bit2CheckBox.Checked = False
1345	rstckbx.Checked = True
1346	End If
1347	If rstckbx.Checked = True Then
1348	'Digital Resets part 2 below
1349	System.Windows.Forms.Cursor.Current = Cursors.WaitCursor
1350	Dim digitalWriteTask As Task = Nothing
1351	Try
1352	digitalWriteTask = New Task()
1353	digitalWriteTask.DOChannels.CreateChannel("Dev1/Port0/line0:7", "port0", _
1354	ChannelLineGrouping.OneChannelForAllLines)
1355	Dim dataArray(7) As Boolean
1356	CheckLines(dataArray)
1357	Dim writer As New DigitalSingleChannelWriter(digitalWriteTask.Stream)
1358	writer.WriteSingleSampleMultiLine(True, dataArray)
1359	Catch exception As DaqException

1360	MessageBox.Show(exception.Message)
1361	Finally
1362	digitalWriteTask Dispose()
1363	System Windows Forms Cursor Current – Cursors Default
1303	System. whidows.rorms.Cursor.Current – Cursors.Default
1364	End Try
1365	rstckbx.Checked = False
1366	End If
1367	Catch exception As DaqException
1368	'Dispose the Task and Disable the Timer
1369	loopTimer.Enabled = False
1370	myTask.Dispose()
1371	MessageBox Show(exception Message)
1372	End Try
1373	eventnumber = eventnumber + 3
1374	End Sub
1375	Private Sub Timer1_Tick(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles Timer1.Tick
1376	Timer1.Interval = boxtimer.Value
1377	If motortimer = 1 Then
1378	Out(888, 3)
1379	' If harsten Value – O Then
1377	'Out(202 10)
1201	
1381	End II
1382	hoxport Text = 3
1302	boyfine Taxt $=$ boyfine Taxt ± 1
1305	borfull Value – borfull Value + 1
1204	barten Value – barten Value + 1
1385	barstep. value = barstep. value + 1
1386	If barfull.Value = 200 Then
1387	barfull.Value = 0
1388	Out(888, 19)
1389	PrintLine(1, "beam-on" & " " & time)
1390	TextBox1 AppendText("beam-on" & "" & time & vbCrI f)
1301	boxcomfull Taxt = boxcomfull Taxt = 1
1202	$\Gamma_{\rm eff}$
1392	End II
1393	Labelbarfull.Text = Format\$(barfull.Value / 200 * 100, "00.0")
1394	Labelbarstep.Text = Format $(barstep.Value / 50 * 100, "00.0")$
1395	If barstep.Value = 51 Then
1396	PrintLine(1, "stepped" & " " & time)
1397	TextBox1.AppendText("stepped" & "
1398	barstep. Value = 0
1399	timerstep Interval = halflife Value * 1000
10//	

1400	timerstep.Enabled = True
1401	loopTimer.Enabled = True
1402	Timer1.Enabled = False
1403	End If
1404	End If
1405	If motortimer = 2 Then
1406	Out(888, 6)
1407	'If barstep.Value = 0 Then
1408	'Out(888, 22)
1409	'End If
1410	boxport.Text = 6
1411	boxtfire.Text = boxtfire.Text + 1
1412	barfull.Value = barfull.Value + 1
1413	barstep.Value = barstep.Value + 1
1414	If barfull.Value = 200 Then
1415	barfull.Value $= 0$
1416	Out(888, 22)
1417	PrintLine(1, "beam-on" & " " & time)
1418	TextBox1.AppendText("beam-on" & "
1419	boxcomfull.Text = boxcomfull.Text + 1
1420	End If
1421	Labelbarfull.Text = Format\$(barfull.Value / 200 * 100, "00.0")
1422	Labelbarstep.Text = Format\$(barstep.Value / 50 * 100, "00.0")
1423	If barstep.Value = 51 Then
1424	PrintLine(1, "stepped" & " " & time)
1425	TextBox1.AppendText("stepped" & " " & time & vbCrLf)
1426	barstep.Value = 0
1427	timerstep.Interval = halflife.Value * 1000
1428	timerstep.Enabled = True
1429	loopTimer.Enabled = True
1430	Timer1.Enabled = False
1431	End If
1432	End If
1433	If motortimer = 3 Then
1434	Out(888, 12)
1435	' If barstep. Value = 0 Then
1436	'Out(888, 28)
1437	'End If
1438	boxport.Text = 12
1439	boxtfire.Text = boxtfire.Text + 1
1440	barfull.Value = barfull.Value + 1
1441	barstep.Value = barstep.Value + 1
1442	If barfull.Value = 200 Then
1443	barfull.Value = 0
1444	Out(888, 28)
1445	PrintLine(1, "beam-on" & " " & time)

1446	TextBox1.AppendText("beam-on" & " " & time & vbCrLf)
1447	boxcomfull.Text = $boxcomfull$.Text + 1
1448	End If
1449	Labelbarfull Text = Format\$(barfull Value / 200 * 100 "00 0")
1/150	Labelbarsten Text – Format\$(barsten Value / 50 * 100, "00.0")
1450	Eaberbarstep. rest = $10111at\phi(barstep. value / 50 - 100, 00.0)$
1451	If baratan Valua – 51 Than
1451	DrintLing(1 "stopped" & " " & time)
1452	TextDex1 Among dText("stepped & & & unite)
1455	lexitox1.AppendText(stepped & & & time & voCrL1)
1454	barstep. value = 0
1455	timerstep.interval = naifilite.value * 1000
1456	timerstep. Enabled = $1rue$
1457	loop Timer.Enabled = True
1458	Timer I. Enabled = False
1459	End If
1460	End If
1461	If motortimer = 4 Then
1462	Out(888, 9)
1463	If barstep. Value = 0 Then
1464	Out(888, 25)
1465	End If
1400	
1400	boxport. Text = 9 $h_{\text{ext}} = 1$
1467	boxtrife. lext = boxtrife. lext + 1
1468	bartull. Value = bartull. Value + 1
1469	barstep. Value = barstep. Value + 1
1470	If herfull Velue - 200 Then
1470	If barroull, value = 200 Then barfoll Value = 0
14/1	Darrun. value = 0 O_{1} (2000, 25)
1472	Out(888, 25)
14/3	PrintLine(1, beam-on & & time)
14/4	textBox1.Append1ext(beam-on & & & time & vbCrL1)
14/5	boxcomruii. 1ext = boxcomruii. 1ext + 1
14/6	End If
1 477	$L_{1} = \frac{1}{2} \frac{1}$
14// 1470	Labelbartun. Text = Format\$(bartun. value / $200 \times 100, 00.0$)
14/0	Laberbarstep. rext = Formats(barstep. value / 50 · 100, 00.0)
1470	If harston Value -51 Then
14/9	DrintLing(1 "stanged" & " " & time)
1400	TaxtBax1 Append Taxt("stapped" & " & time & thCrI f)
1401	hereten Value – 0
1402	balstep. value = 0 timerator Interval = halflife Value * 1000
1483	timerstep.interval = naimie. value * 1000
1484	timerstep.Enabled = Irue
1485	100p 1 mer. Enabled = 1 rue
1486	IimerI.Enabled = False
1487	
1488	End II
1490	motortimor – motortimor 1
1409 1400	motorumer = motorumer + 1
1490 1401	motortimer = 3 men
1471 1402	$\frac{1}{1}$
1492	EIIQ II

- 1493 End Sub
- Private Sub timerstep_Tick(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles
 timerstep.Tick

1496	barstep.Value $= 0$
1497	Labelbarstep.Text = timerstep.Interval
1498	If boxport.Text = "3" Then
1499	motortimer = 1
1500	Timer1.Enabled = $True$
1501	End If
1502	If boxport.Text = "6" Then
1503	motortimer = 2
1504	Timer1.Enabled = $True$
1505	End If
1506	If boxport.Text = "12" Then
1507	motortimer = 3
1508	Timer1.Enabled = $True$
1509	End If
1510	If boxport.Text = "9" Then
1511	motortimer = 4
1512	Timer1.Enabled = $True$
1513	End If
1514	loopTimer.Enabled = False
1515	timerstep.Enabled = False
1516	End Sub
1517	Private Sub stopbutton2_Click(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles
1518	stopbutton2.Click
1519	Timer1.Enabled = False
1520	timerstep.Enabled = False
1521	'DAQ Stop Actions
1522	Dispose the Task and Disable the Timer
1523	loopTimer.Enabled = False
1524	myTask.Dispose()
1525	FileClose(1)
1526	End Sub
1527	Private Sub Button2_Click(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles
1528	Button2.Click
1529	Out(888, 3)
1530	End Sub
1531	Private Sub Button3_Click(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles
1532	Button3.Click
1533	Out(888, 6)
1534	End Sub
1535	Private Sub Button4_Click(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles
1536	Button4.Click
1537	Out(888, 12)
1538	End Sub

1539	Private Sub Button5_Click(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles
1540	Button5.Click
1541	Out(888, 9)
1542	End Sub
1543	Private Sub reset_Click(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles reset.Click
1544	Out(888, 0)
1545	End Sub
1546	Private Sub Button6_Click(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles
1547	Button6.Click
1548	boxtfire.Text = 0
1549	barfull.Value = 0
1550	Labelbarfull.Text = 0.0
1551	barstep. Value $= 0$
1552	boxport. Text = 0
1553	End Sub
1554	Private Sub Button1 Click(ByVal sender As System,Object, ByVal e As System,EventArgs) Handles
1555	Button1.Click
1556	'Digital Resets Prevariables
1557	'Stepper Prevariables
1558	Timer1.Enabled = True
1559	'DAQ Prevariables
1560	FileOpen(1, tbfilename.Text, OpenMode.Append)
1561	beamstate = 0
1562	acquiredSamplesCount = 0
1563	Try
1564	Create a new task
1565	myTask = NewTask()
1566	Create a virtual channel
1567	myTask.AIChannels.CreateVoltageChannel(physicalChannelComboBox.Text, "", _
1568	AITerminalConfiguration.Rse, Convert.ToDouble(minimumValueNumeric.Value), _
1569	Convert.ToDouble(maximumValueNumeric.Value), AIVoltageUnits.Volts)
1570	'Verify the Task
1571	myTask.Control(TaskAction.Verify)
1572	reader = New AnalogMultiChannelReader(myTask.Stream)
1573	'enable the timer
1574	'loopTimer.Enabled = True
1575	Catch exception As DaqException
1576	Dispose the Task and Disable the Timer
1577	loopTimer.Enabled = False
1578	myTask.Dispose()
1579	MessageBox.Show(exception.Message)
1580	End Try
1581	End Sub
1582	Private Sub HelpToolStripMenuItem_Click(ByVal sender As System.Object, ByVal e As System.EventArgs)

- Handles HelpToolStripMenuItem.Click MsgBox("If you clicked this then you obviously don't know what your doing and you need to call either Mitch

- 1585 at (510)684-8092 or Maz at (925)286-4907 immediately!", , "You've really done it now...")
- 1586 End Sub
- 1587 Private Sub samples100_Tick(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles 1588 samples100.Tick
- 1589 End Sub
- 1590 Private Sub CheckLines(ByRef dataArray() As Boolean)
- 1591 dataArray(0) = bit0CheckBox.Checked
- 1592 dataArray(1) = bit1CheckBox.Checked
- 1593 dataArray(2) = bit2CheckBox.Checked
- 1594dataArray(3) = bit3CheckBox.Checked1595dataArray(4) = bit4CheckBox.Checked
- 1595 dataArray(4) = bit4CheckBox.Checked1596 dataArray(5) = bit5CheckBox.Checked
- 1597 dataArray(6) = bit6CheckBox.Checked dataArray(6) = bit6CheckBox.Checked
- 1598 dataArray(7) = bit7CheckBox.Checked
- 1599 End Sub
- Private Sub writeButton_Click(ByVal sender As System.Object, ByVal e As System.EventArgs) Handles 1600 1601 writeButton.Click System.Windows.Forms.Cursor.Current = Cursors.WaitCursor 1602 1603 Dim digitalWriteTask As Task = Nothing 1604 Try digitalWriteTask = New Task() 1605 digitalWriteTask.DOChannels.CreateChannel("Dev1/Port0/line0:7", "port0", _ 1606 1607 ChannelLineGrouping.OneChannelForAllLines) Dim dataArray(7) As Boolean 1608 1609 CheckLines(dataArray) Dim writer As New DigitalSingleChannelWriter(digitalWriteTask.Stream) 1610 1611 writer.WriteSingleSampleMultiLine(True, dataArray) Catch exception As DagException 1612 MessageBox.Show(exception.Message) 1613 1614 Finally 1615 digitalWriteTask.Dispose() System.Windows.Forms.Cursor.Current = Cursors.Default 1616 End Try 1617
- 1618 End Sub
- 1619 End Class

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